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Batz, Jr. et al.

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(45) **Date of Patent: *Jan. 1, 2002**

(54) **APPARATUS FOR HIGH DEPOSITION RATE SOLDER ELECTROPLATING ON A MICROELECTRONIC WORKPIECE**

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(73) Assignee: **Semitool, Inc.**, Kalispell, MT (US)

(*) Notice: This patent issued on a continued prosecution application filed under 37 CFR 1.53(d), and is subject to the twenty year patent term provisions of 35 U.S.C. 154(a)(2).

Subject to any disclaimer, the term of this patent is extended or adjusted under 35 U.S.C. 154(b) by 0 days.

(21) Appl. No.: **09/386,213**

(22) Filed: **Aug. 31, 1999**

Related U.S. Application Data

(63) Continuation of application No. PCT/US99/15850, filed on Jul. 12, 1999.
(60) Provisional application No. 60/114,450, filed on Dec. 31, 1998.

(51) **Int. Cl.**[7] **C25D 17/02**
(52) **U.S. Cl.** .... **204/212**; 204/275.1; 204/277; 204/292; 204/297.01; 204/297.1; 204/224 R; 204/225
(58) **Field of Search** .... 204/224 R, 212, 204/225, 275.1, 277, 292, 297.01, 297.1; 205/299–300

(56) **References Cited**

U.S. PATENT DOCUMENTS

3,716,462 A	2/1973	Jensen
3,878,066 A	4/1975	Dettke et al.
3,930,963 A	1/1976	Polichette et al.
4,137,867 A	2/1979	Aigo
4,246,088 A	1/1981	Murphy et al.
4,259,166 A	3/1981	Whitehurst
4,304,641 A	12/1981	Grandia et al.
4,341,629 A	7/1982	Uhlinger
4,422,915 A	12/1983	Wielonski et al.
4,466,864 A	8/1984	Bacon

(List continued on next page.)

FOREIGN PATENT DOCUMENTS

WO	WO00/32835	of 0000
WO	WO99/25904	of 0000
WO	WO99/25905	5/1999

* cited by examiner

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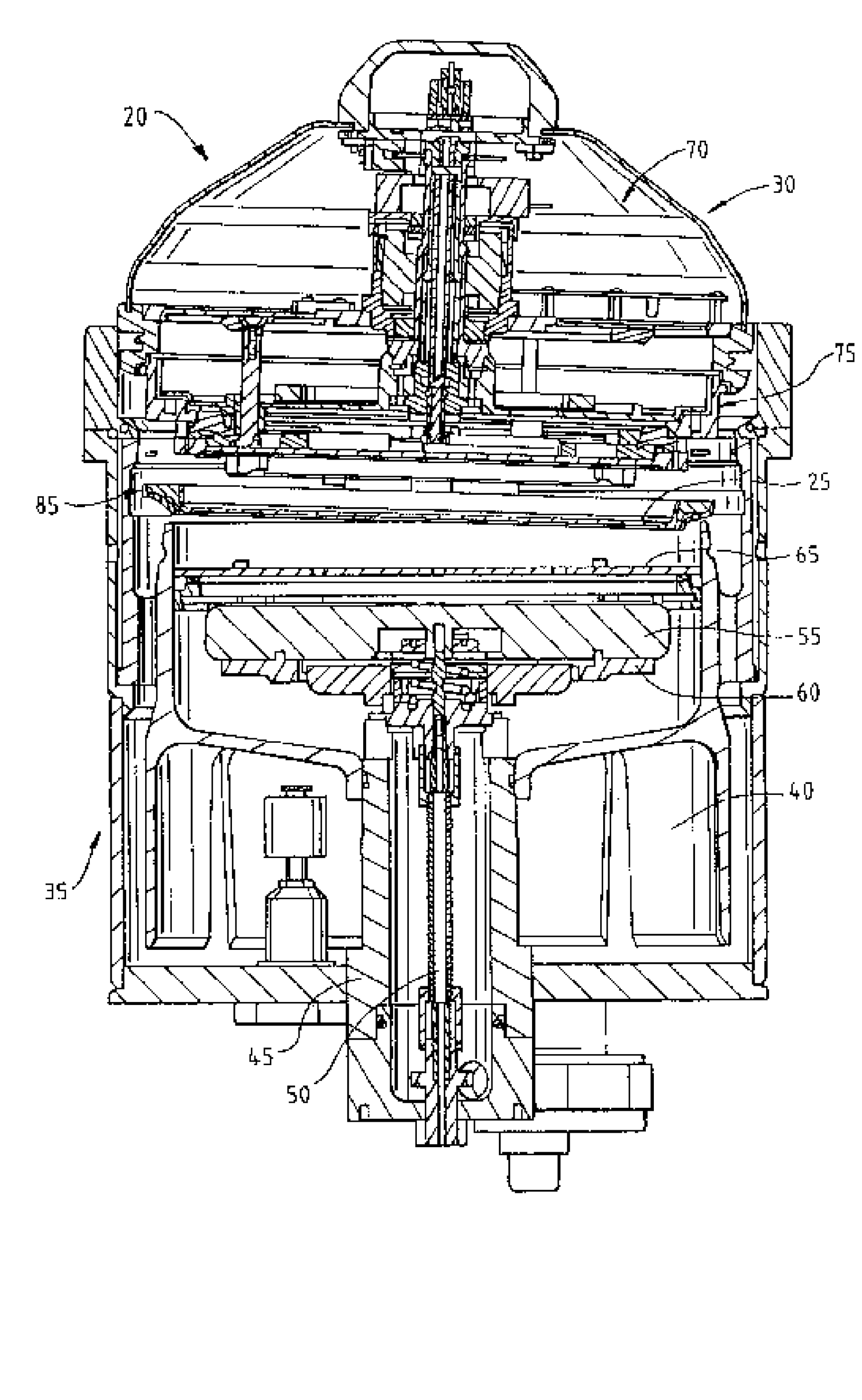
(57) **ABSTRACT**

The present invention is directed to an improved electroplating method, chemistry, and apparatus for selectively depositing tin/lead solder bumps and other structures at a high deposition rate pursuant to manufacturing a microelectronic device from a workpiece, such as a semiconductor wafer. An apparatus for plating solder on a microelectronic workpiece in accordance with one aspect of the present invention comprises a reactor chamber containing an electroplating solution having free ions of tin and lead for plating onto the workpiece. A chemical delivery system is used to deliver the electroplating solution to the reactor chamber at a high flow rate. A workpiece support is used that includes a contact assembly for providing electroplating power to a surface at a side of the workpiece that is to be plated. The contact contacts the workpiece at a large plurality of discrete contact points that isolated from exposure to the electroplating solution. An anode, preferably a consumable anode, is spaced from the workpiece support within the reaction chamber and is in contact with the electroplating solution. In accordance with one embodiment the electroplating solution comprises a concentration of a lead compound, a concentration of a tin compound, water and methane sulfonic acid.

18 Claims, 15 Drawing Sheets



U.S. PATENT DOCUMENTS

4,565,609 A 1/1986 Nobel et al.
4,565,610 A 1/1986 Nobel et al.
4,576,685 A 3/1986 Goffredo et al.
4,576,689 A 3/1986 Makkaey et al.
4,617,097 A 10/1986 Nobel et al.
4,685,414 A 8/1987 DiRico
4,849,059 A 7/1989 Deresh et al.
4,913,085 A 4/1990 Vöhringer et al.
4,959,278 A 9/1990 Shimauchi et al.
5,116,430 A 5/1992 Hirai et al.
5,135,636 A 8/1992 Yee et al.
5,209,817 A 5/1993 Ahmad et al.
5,227,041 A 7/1993 Brogden et al.
5,271,953 A 12/1993 Litteral
5,282,953 A 2/1994 Gernon et al.
5,296,128 A 3/1994 Gernon et al.
5,344,491 A 9/1994 Katou
5,372,848 A 12/1994 Blackwell et al.
5,391,285 A 2/1995 Lytle et al.
5,429,733 A 7/1995 Ishida
5,437,777 A * 8/1995 Kishi .... 204/224 R
5,441,629 A 8/1995 Kosaki
5,443,707 A 8/1995 Mori
5,447,615 A 9/1995 Ishida
5,472,592 A 12/1995 Lowery et al.
5,549,808 A 8/1996 Farooq et al.
5,597,460 A 1/1997 Reynolds
5,597,836 A 1/1997 Hackler et al.
5,609,239 A 3/1997 Schlecker
5,639,316 A 6/1997 Cabral, Jr. et al.
5,651,873 A 7/1997 Uchiyama et al.
5,670,034 A 9/1997 Lowery
5,698,087 A 12/1997 Bokisa
5,744,019 A 4/1998 Ang
5,747,098 A 5/1998 Larson
5,776,327 A 7/1998 Botts et al.
5,788,829 A 8/1998 Joshi et al.
5,807,469 A 9/1998 Crafts et al.
5,843,296 A 12/1998 Greenspan
5,871,626 A * 2/1999 Crafts et al. .... 204/297 R
5,904,827 A 5/1999 Reynolds
5,932,077 A 8/1999 Reynolds
6,001,235 A 12/1999 Arken et al.
6,017,437 A * 1/2000 Ting et al. .... 204/224 R X
6,080,291 A 6/2000 Woodruff et al.

FIG. 1

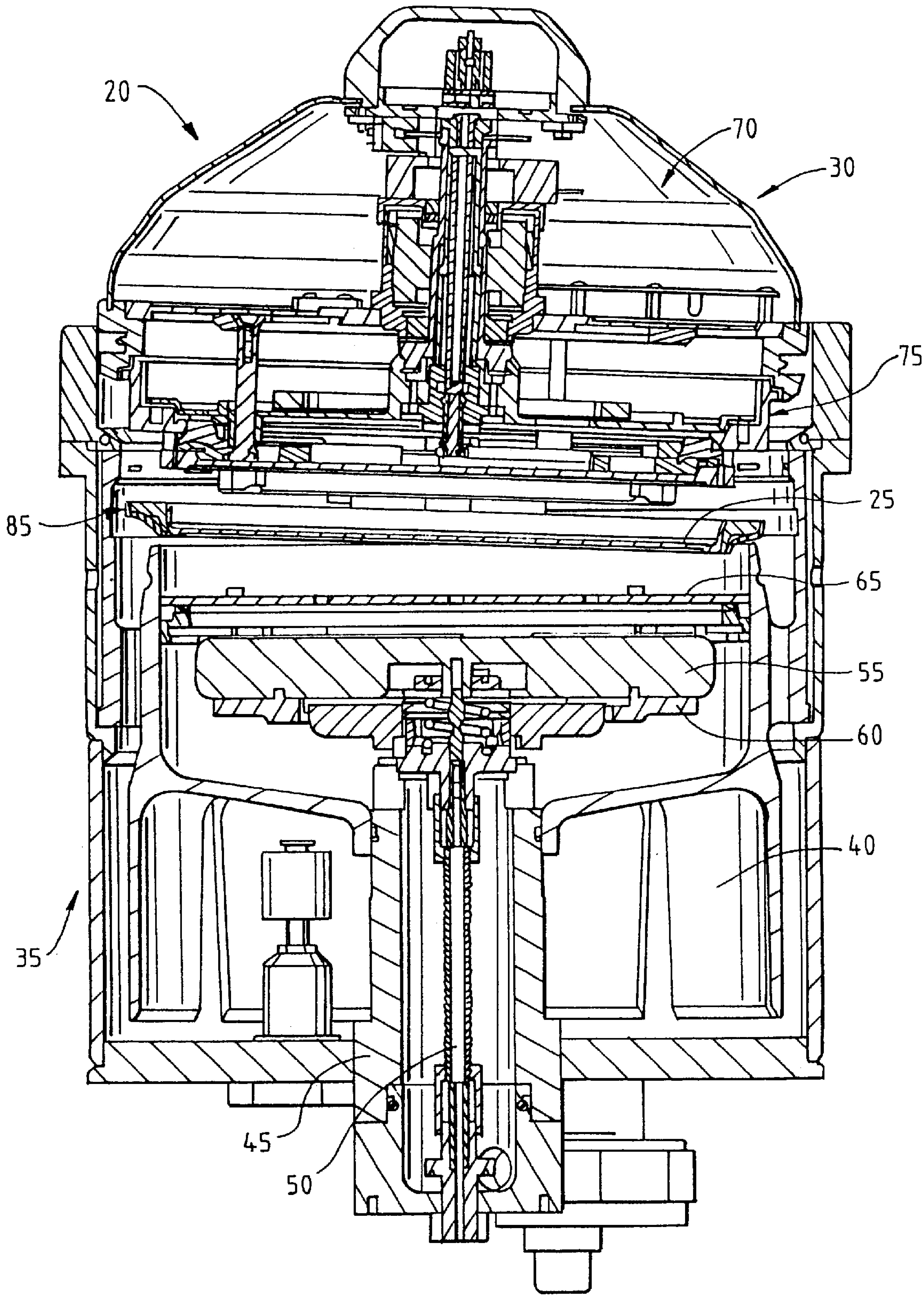


FIG. 2

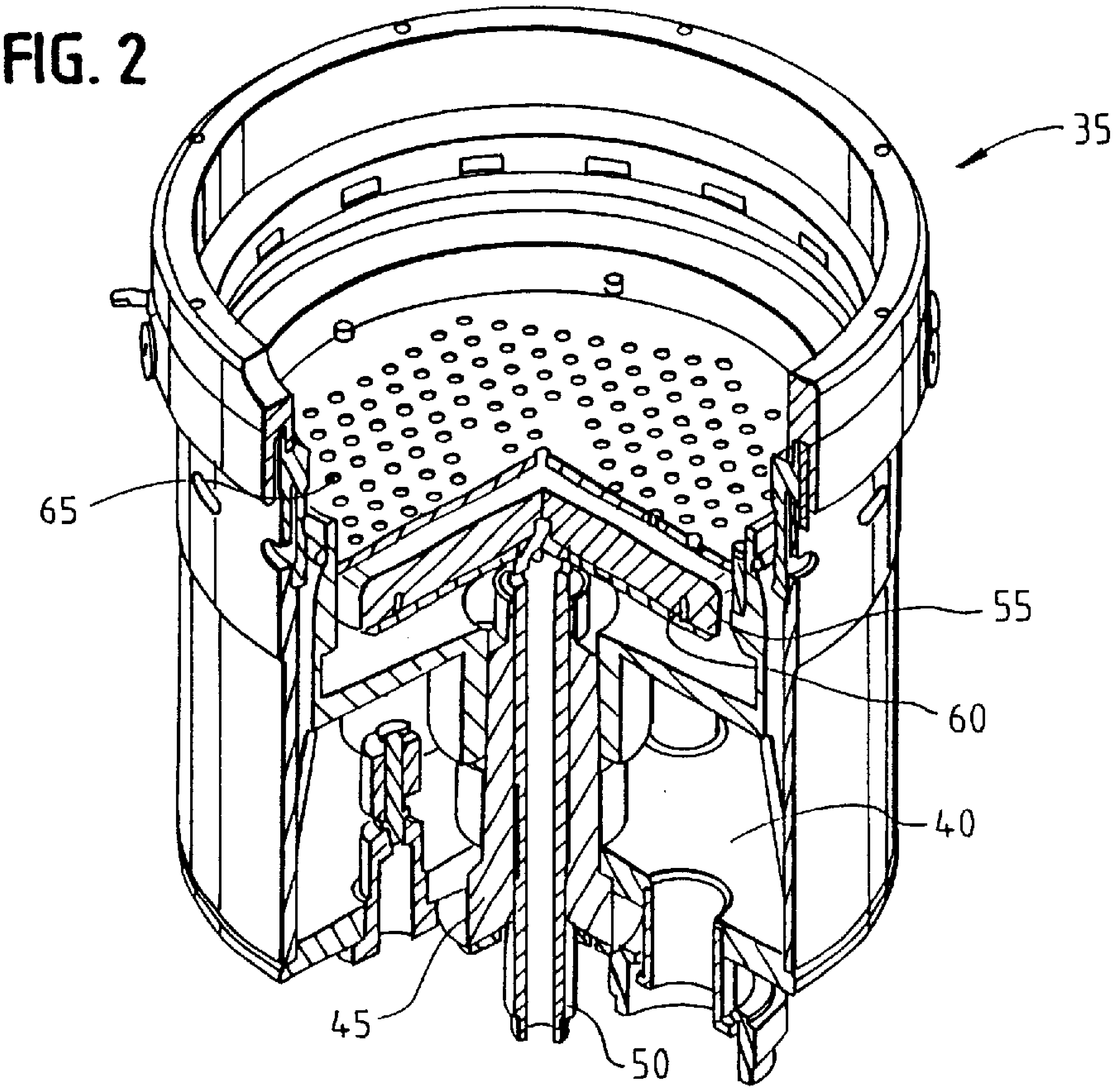


FIG. 3

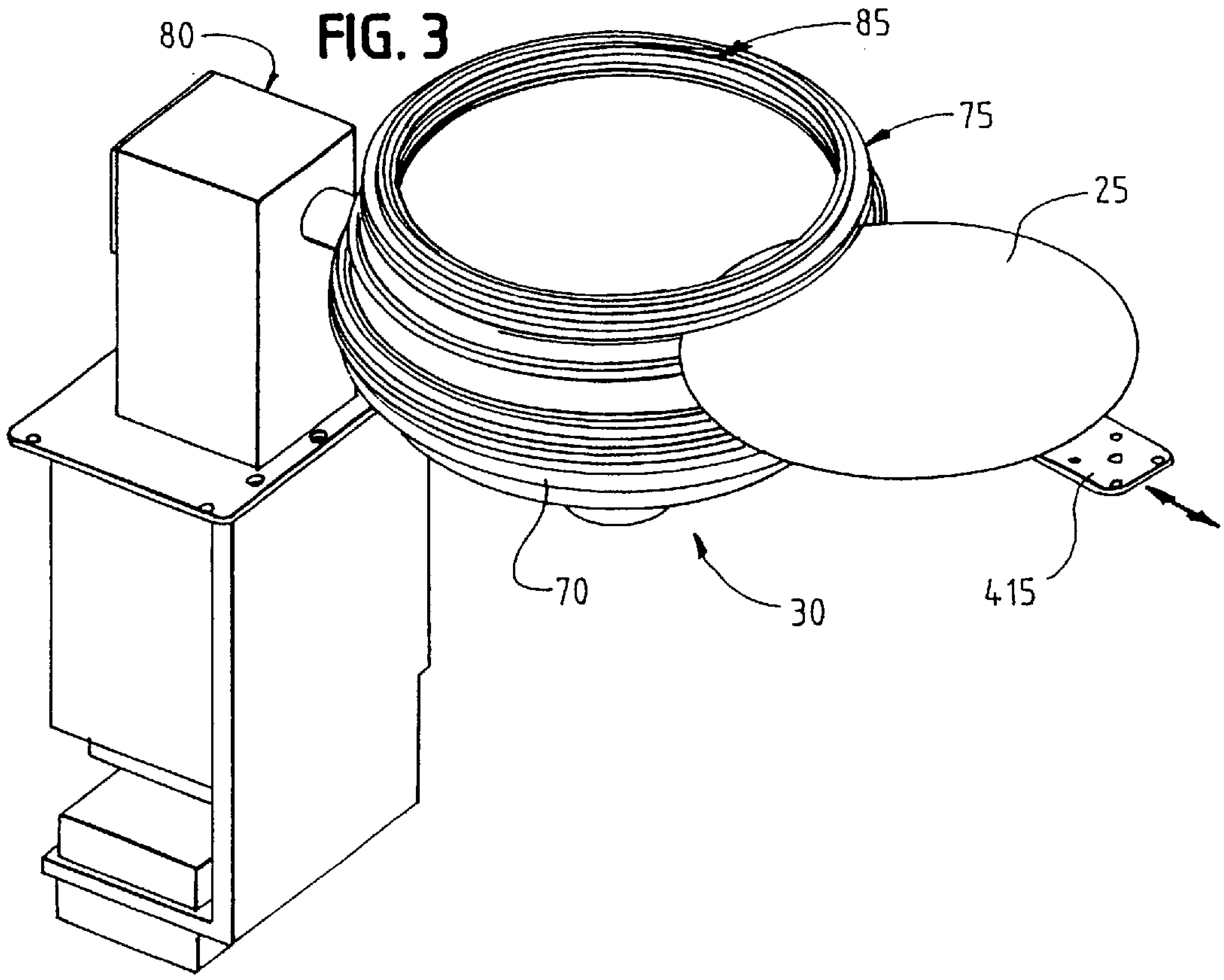


FIG. 4

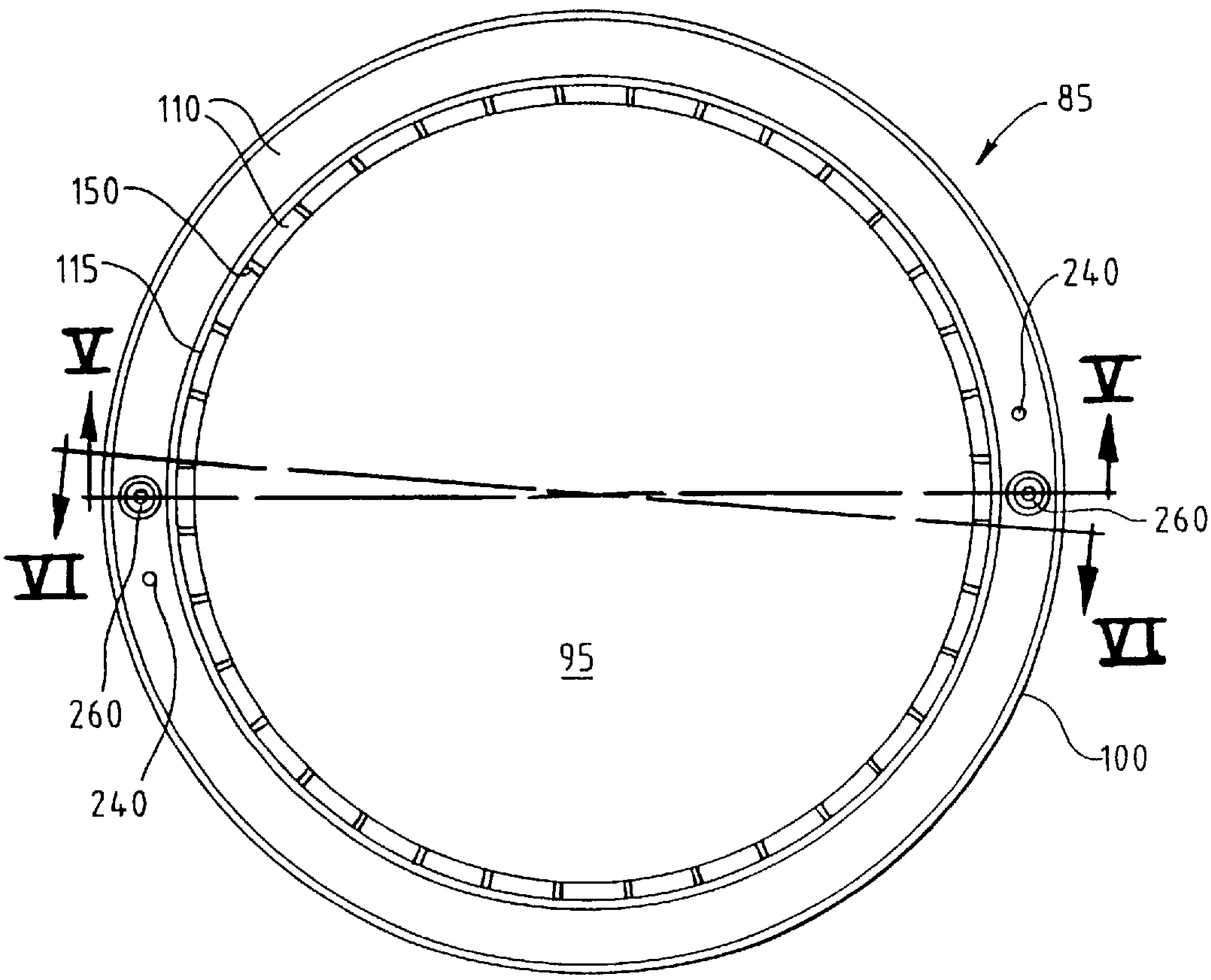


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FIG. 5

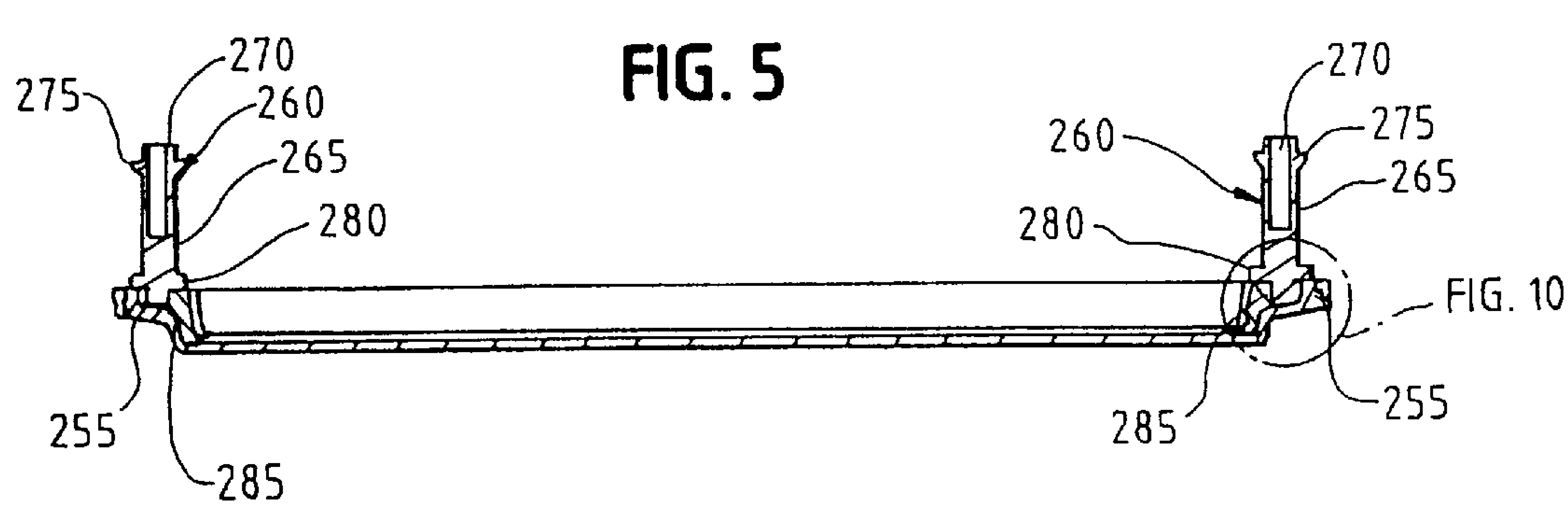

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FIG. 6

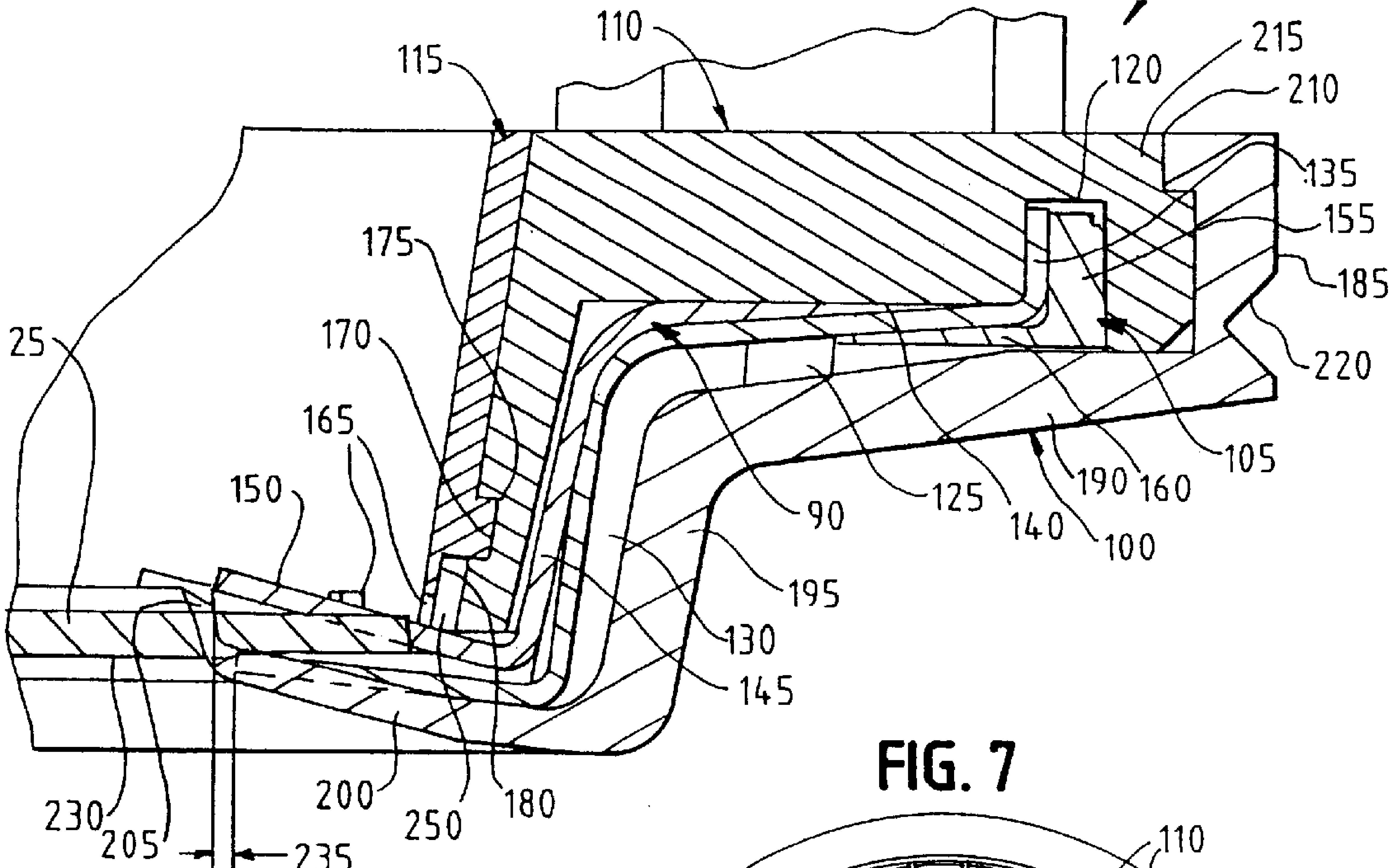

FIG. 7

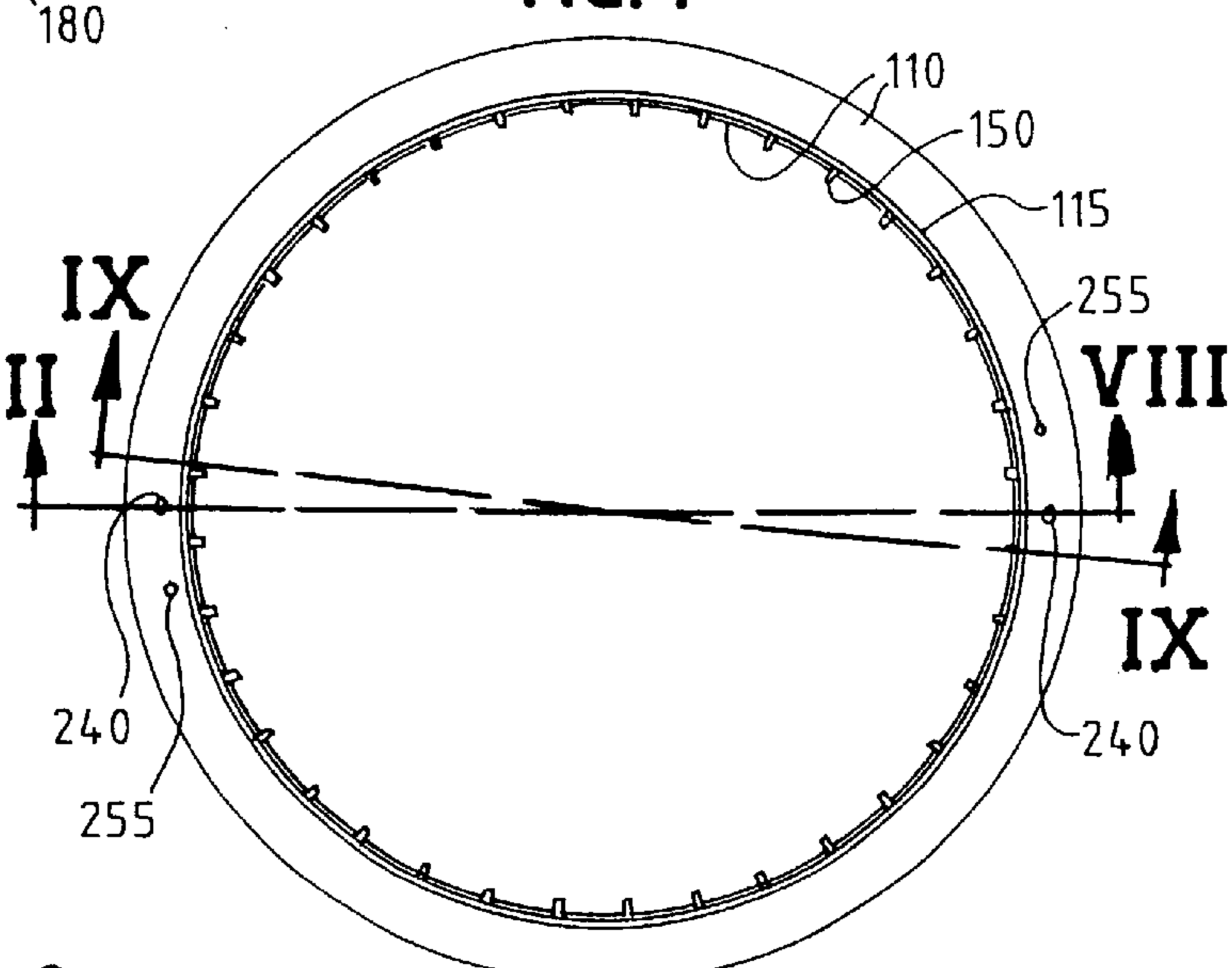

FIG. 8

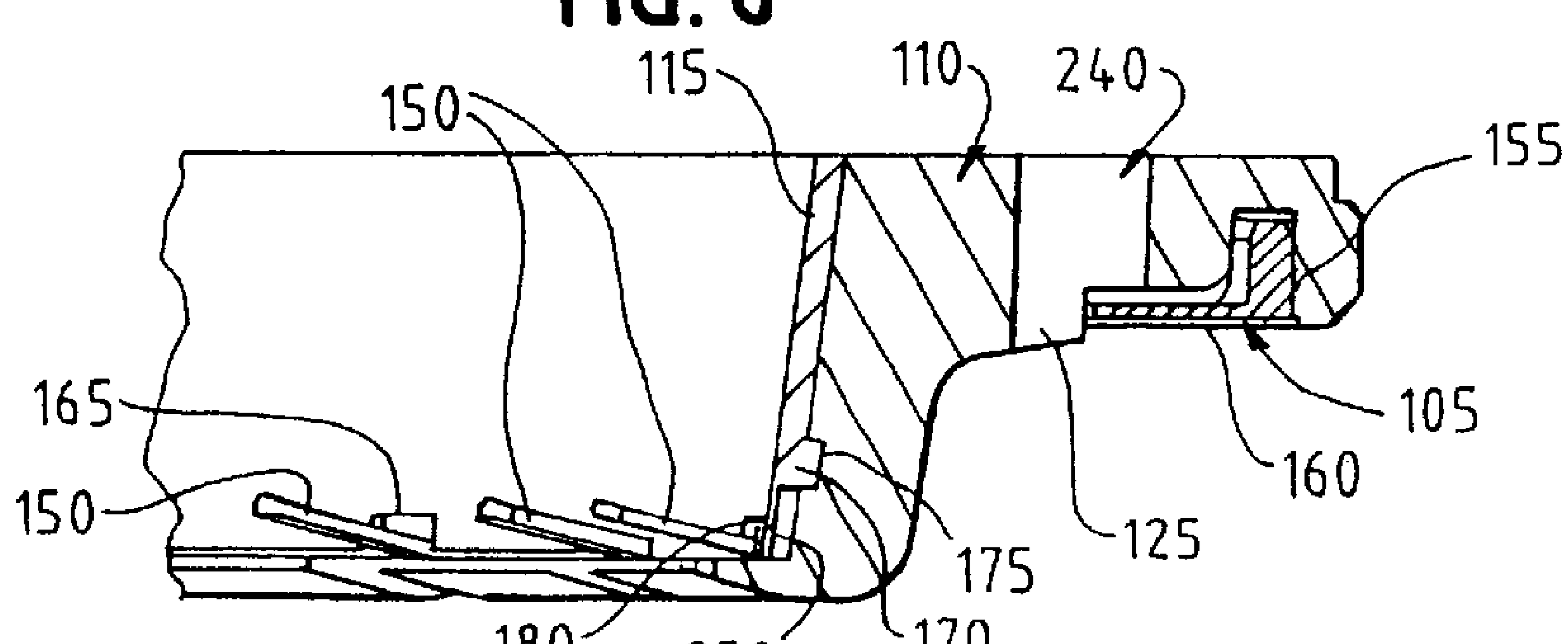

FIG. 9

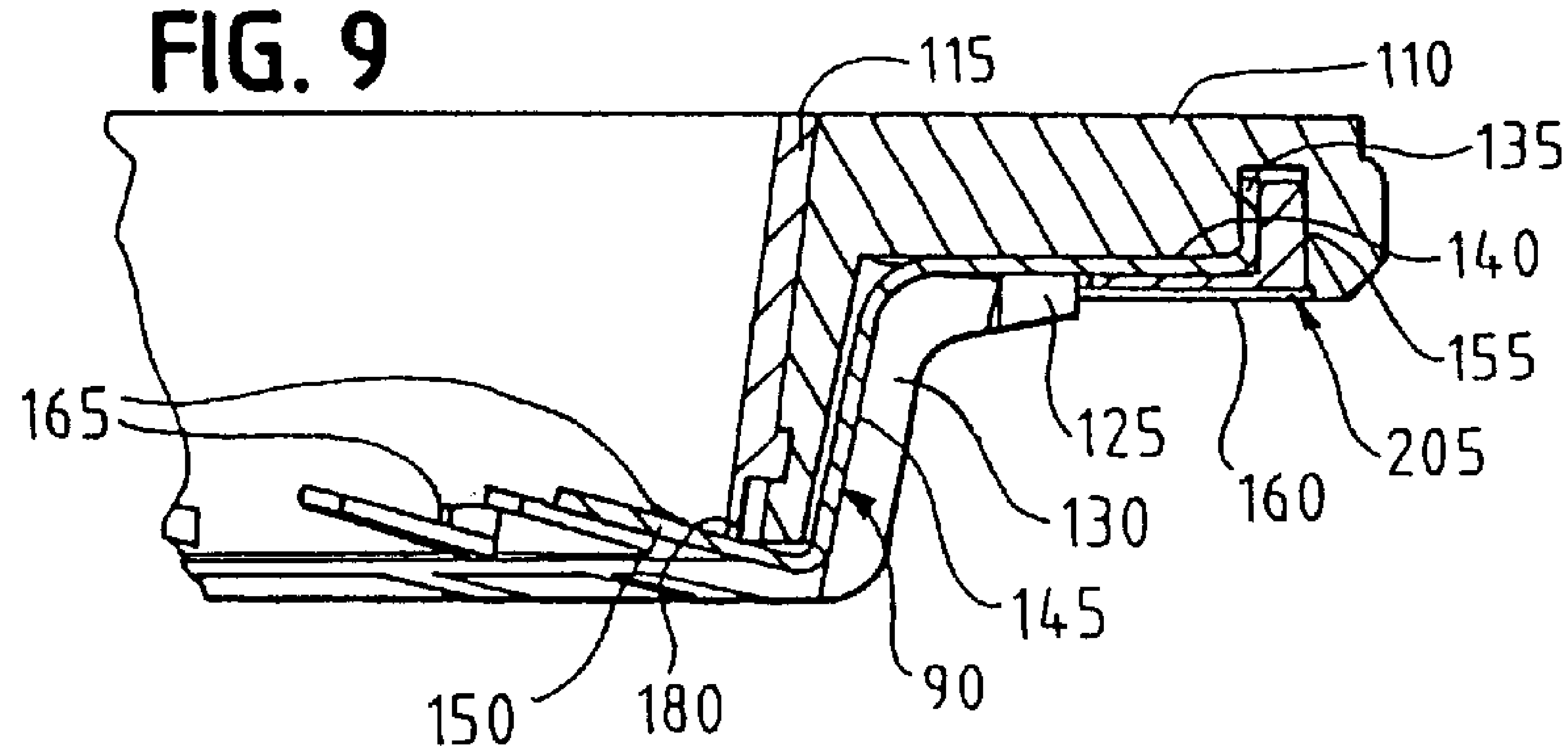

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FIG. 10

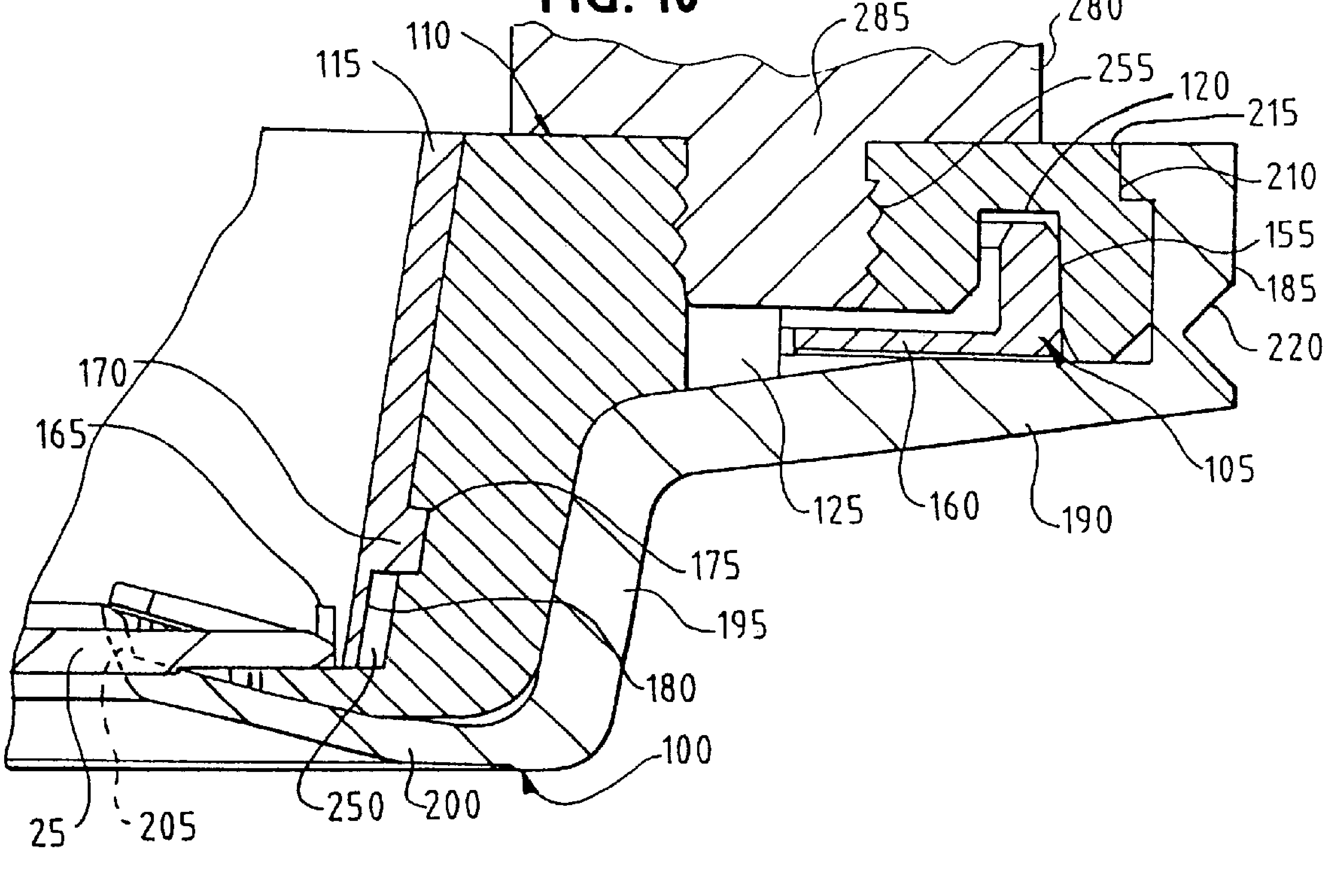

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FIG. 11A

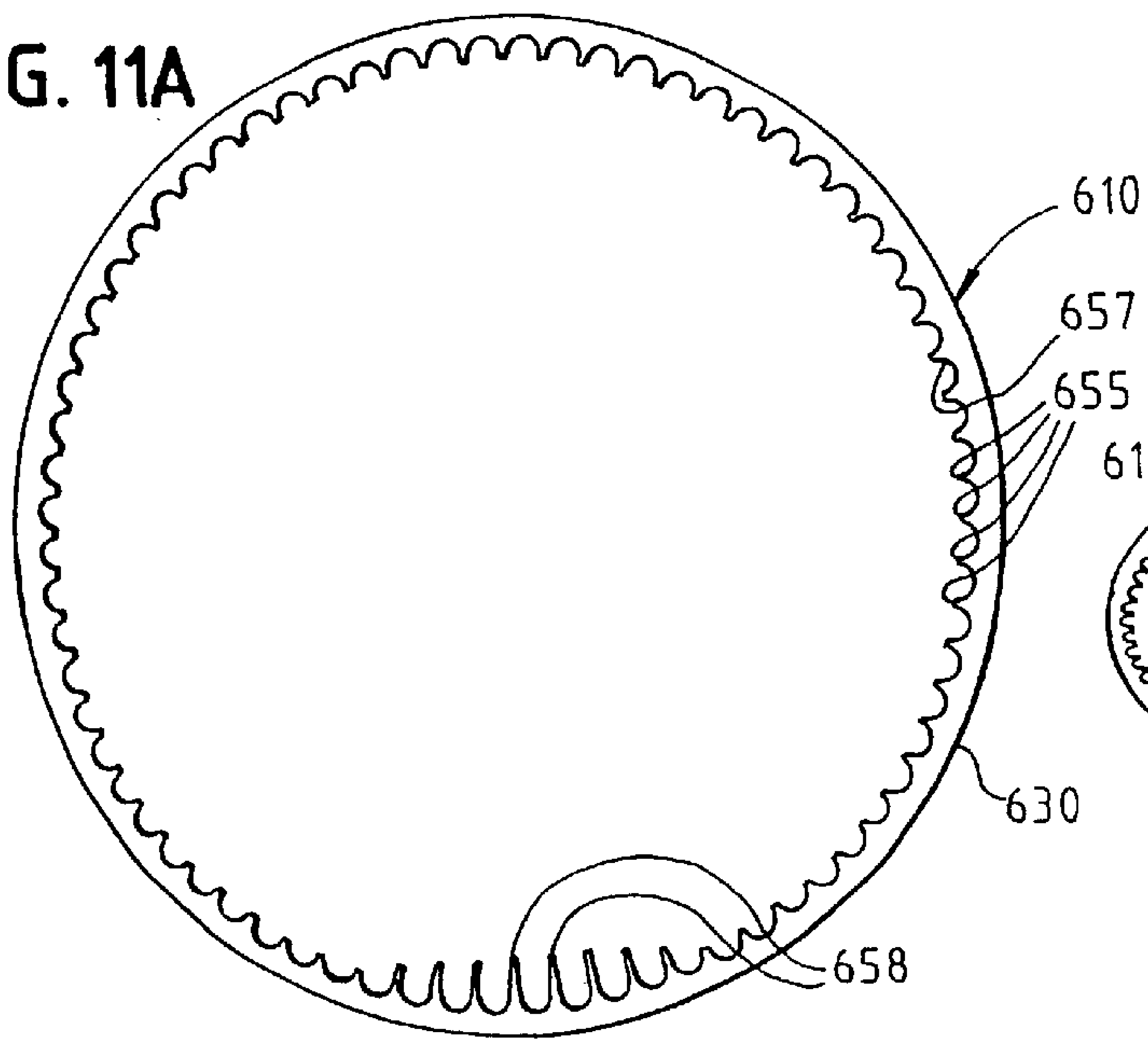

FIG. 11B

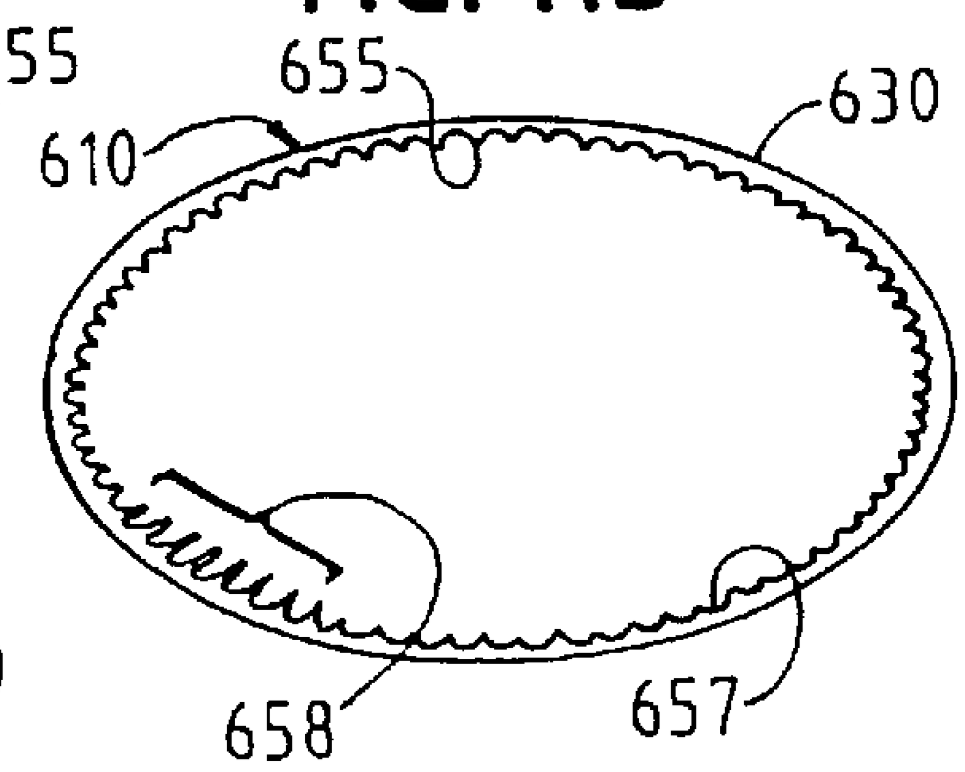

FIG. 12

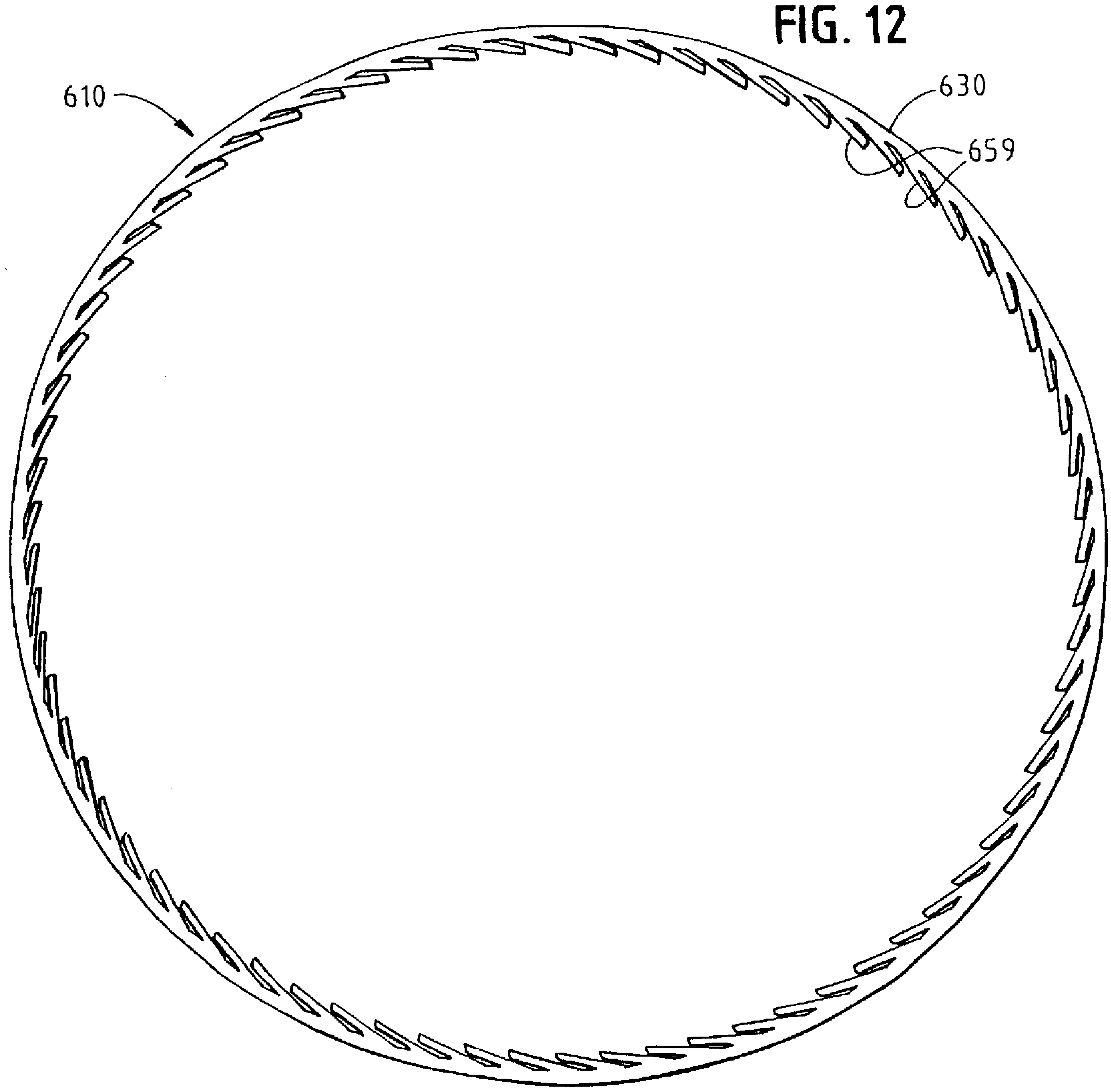

FIG. 13

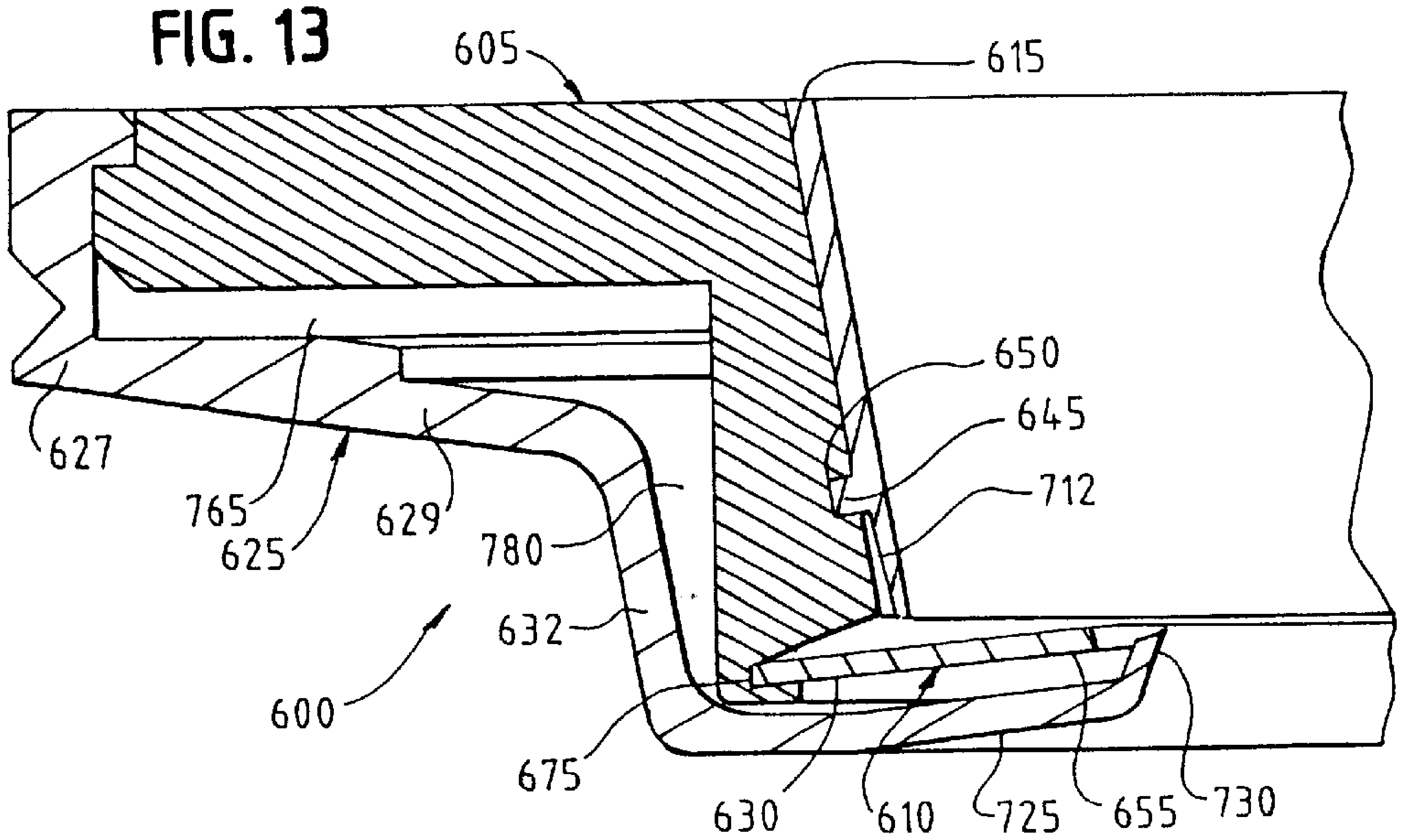

FIG. 14

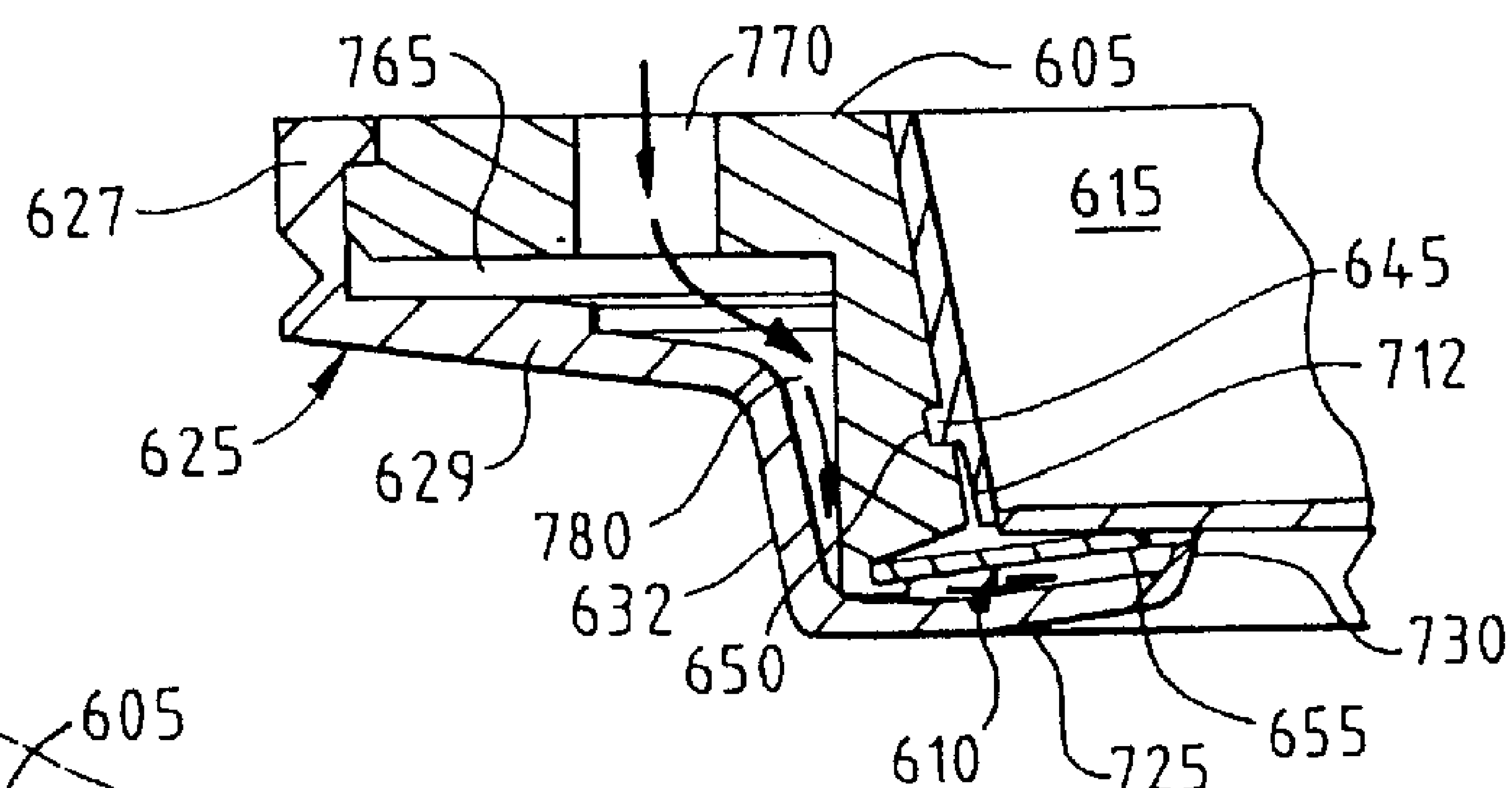

FIG. 15

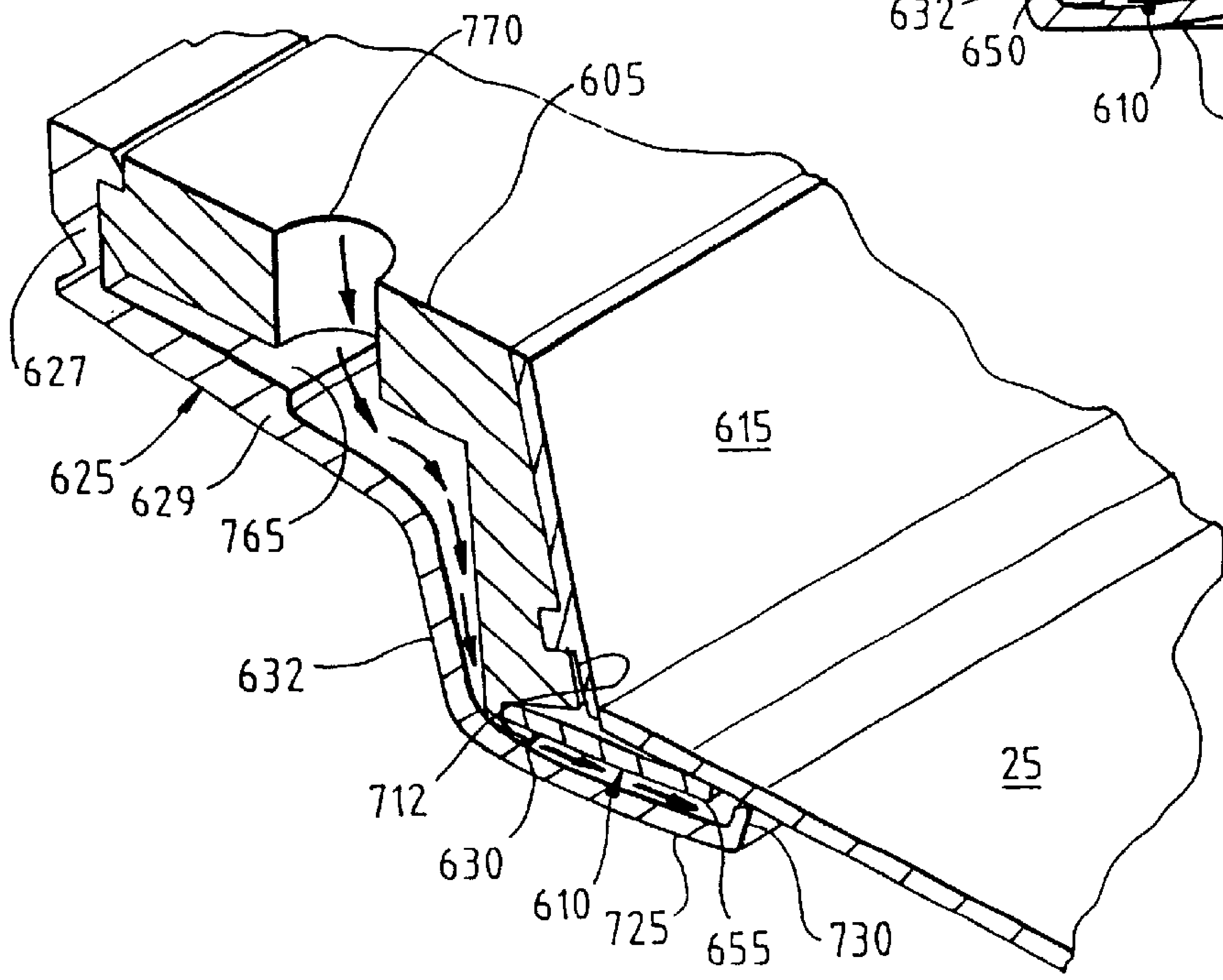

FIG. 16

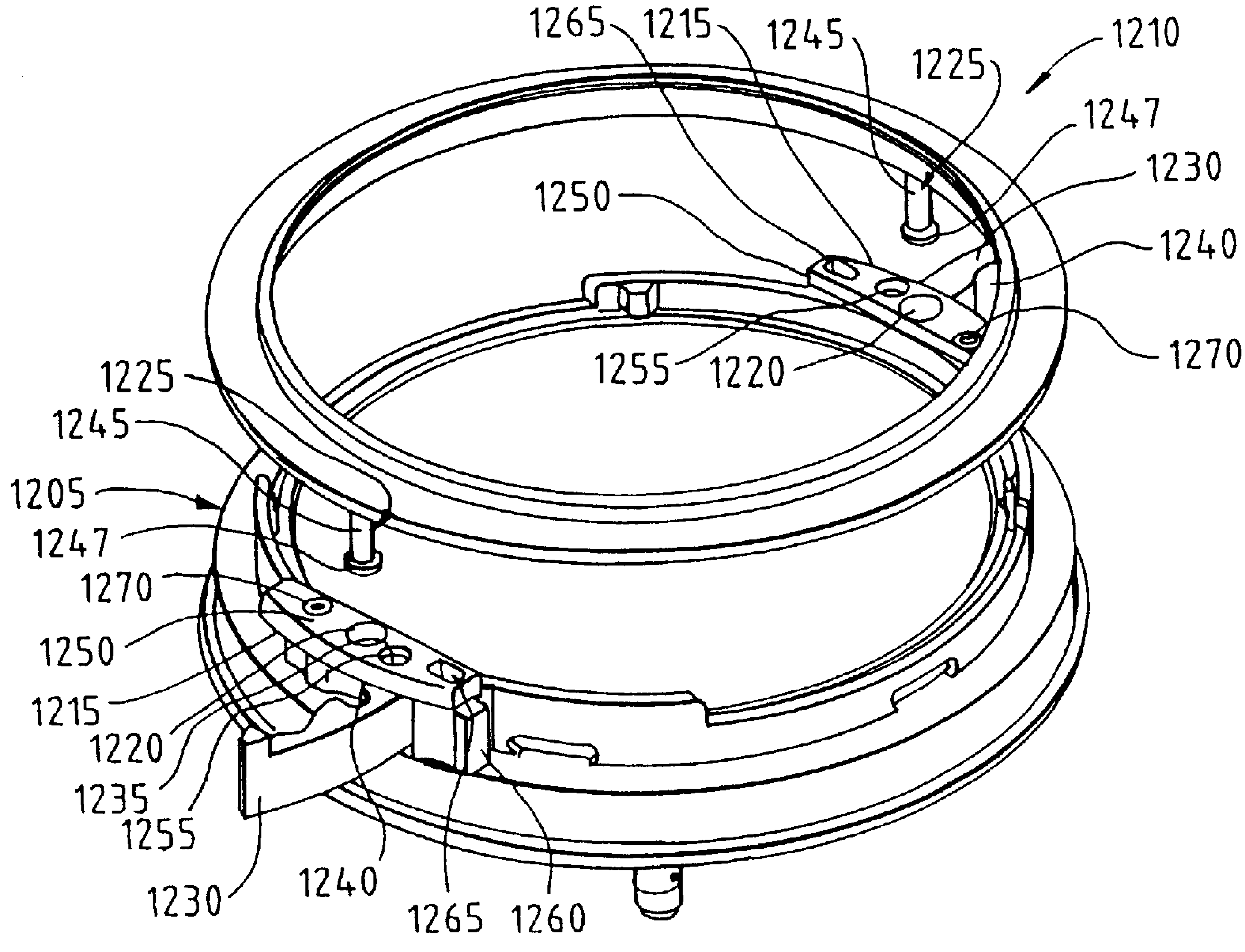
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FIG. 17

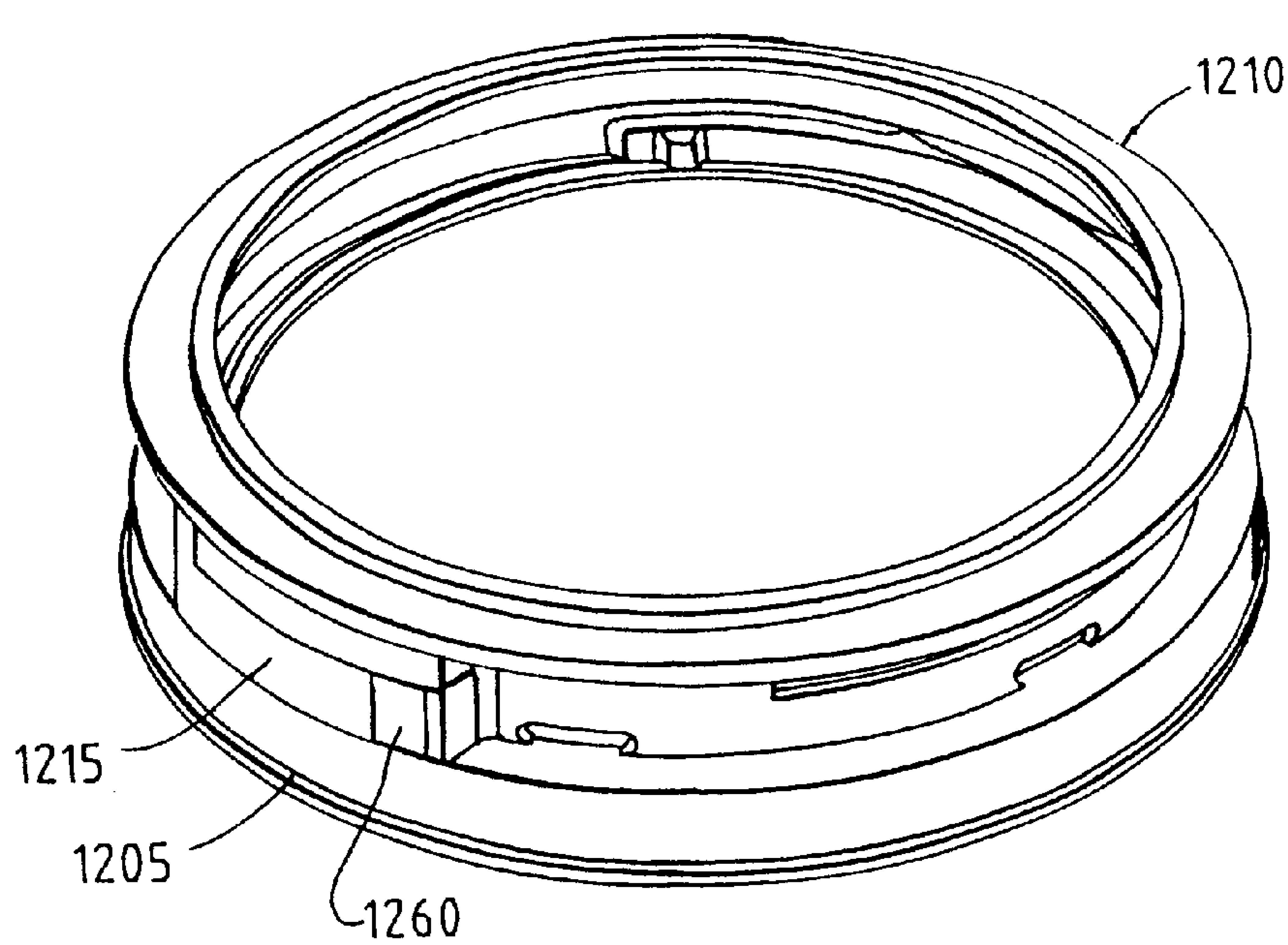
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FIG. 18A

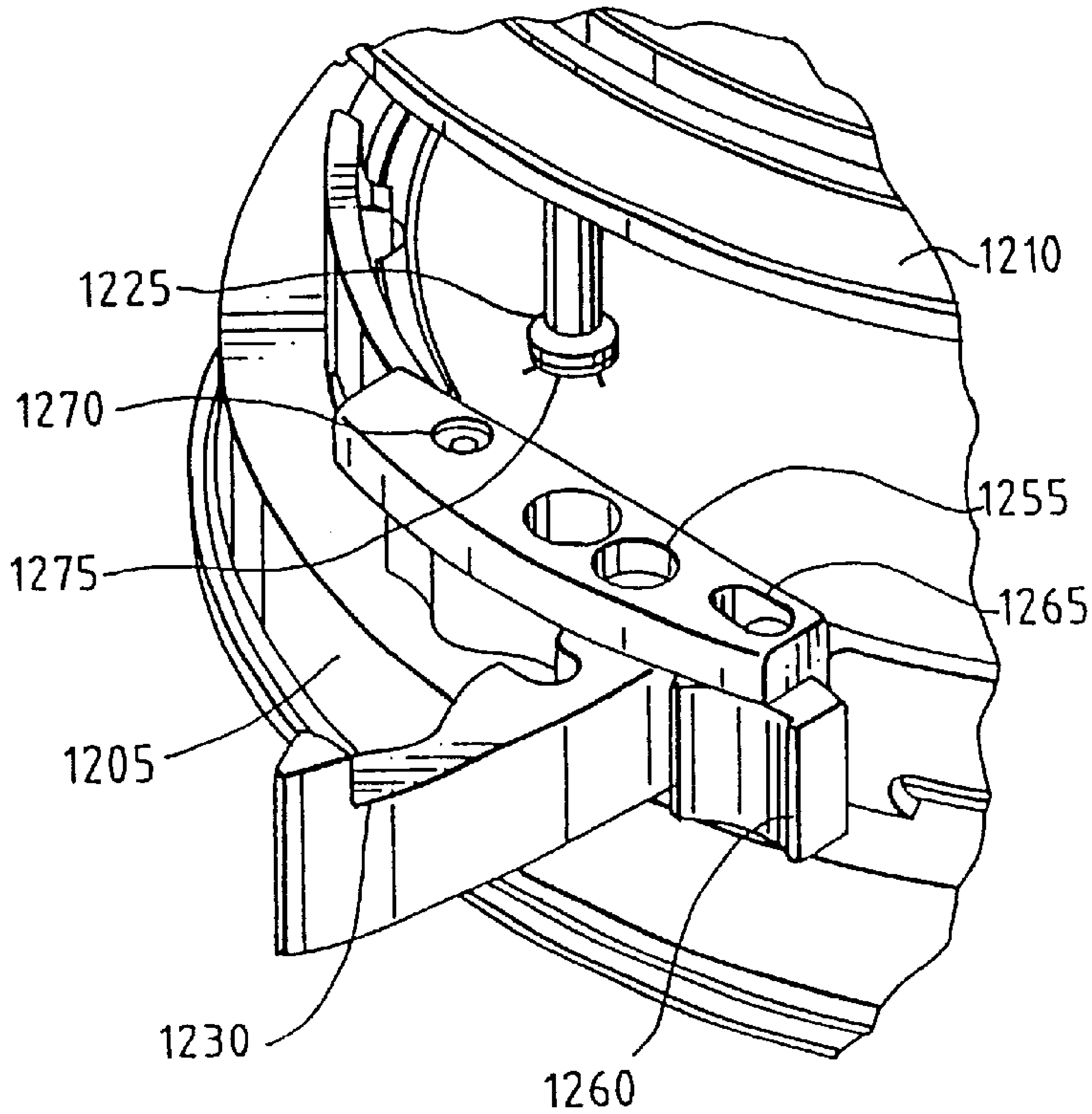


FIG. 18B

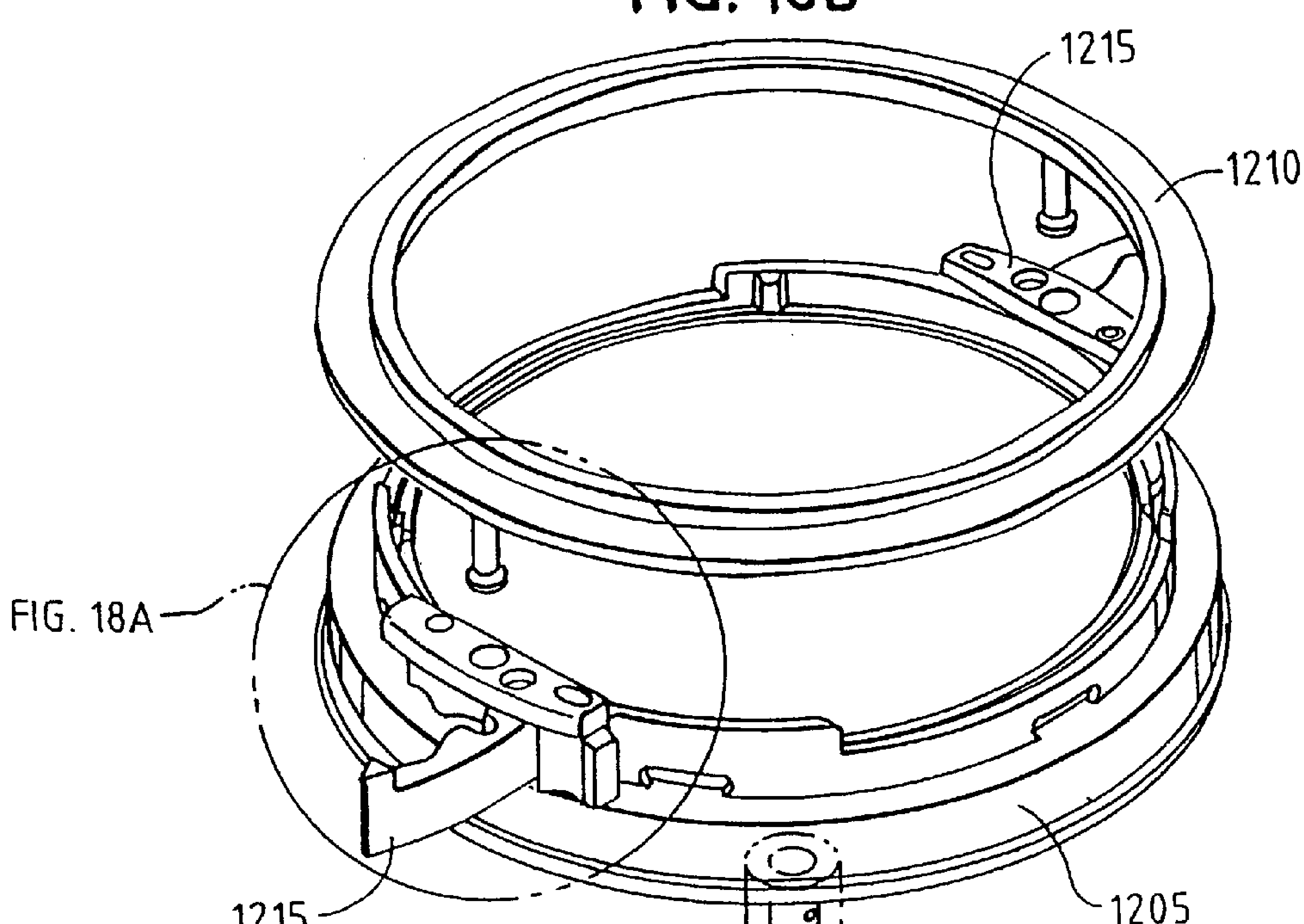


FIG. 19A

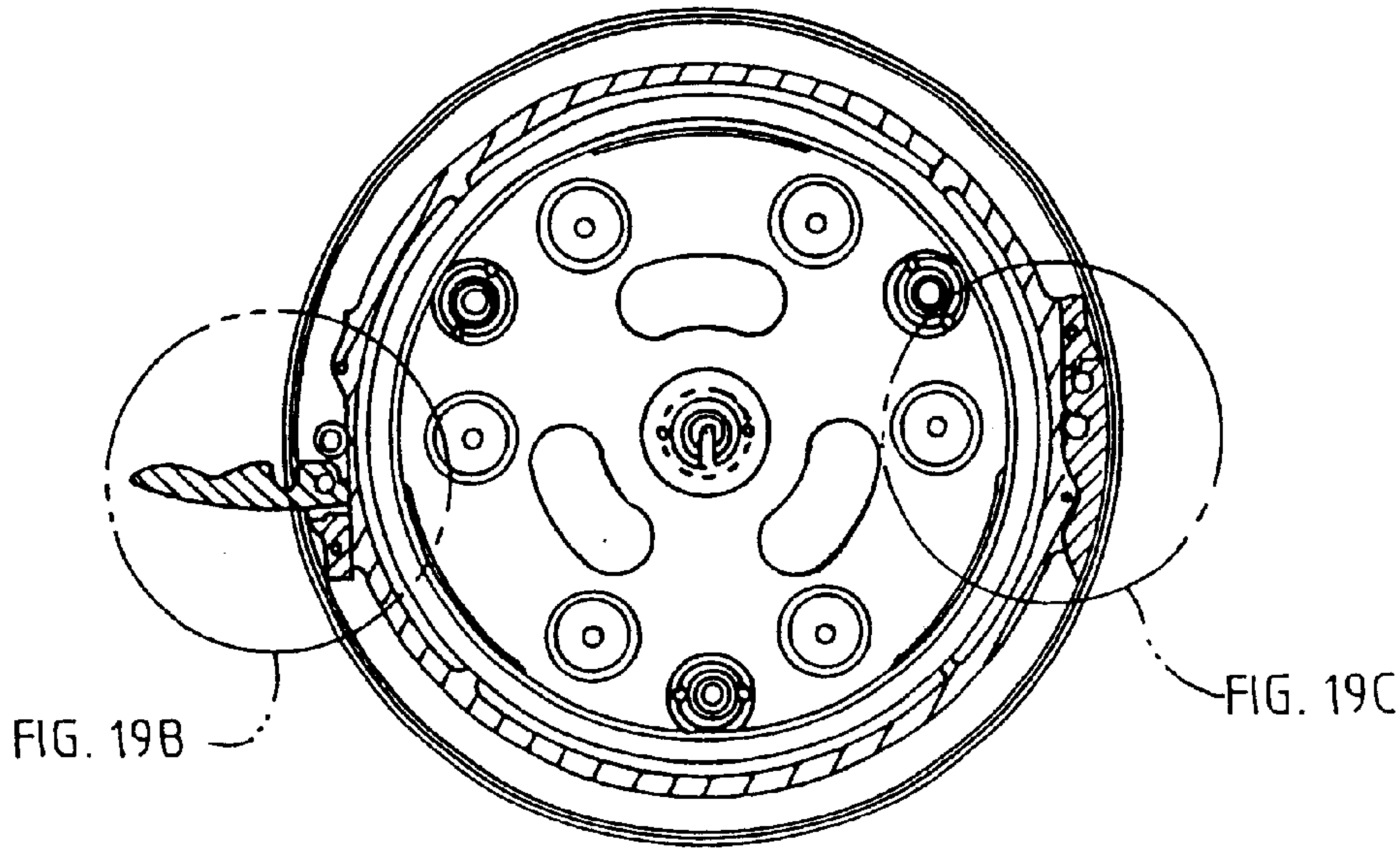


FIG. 19B

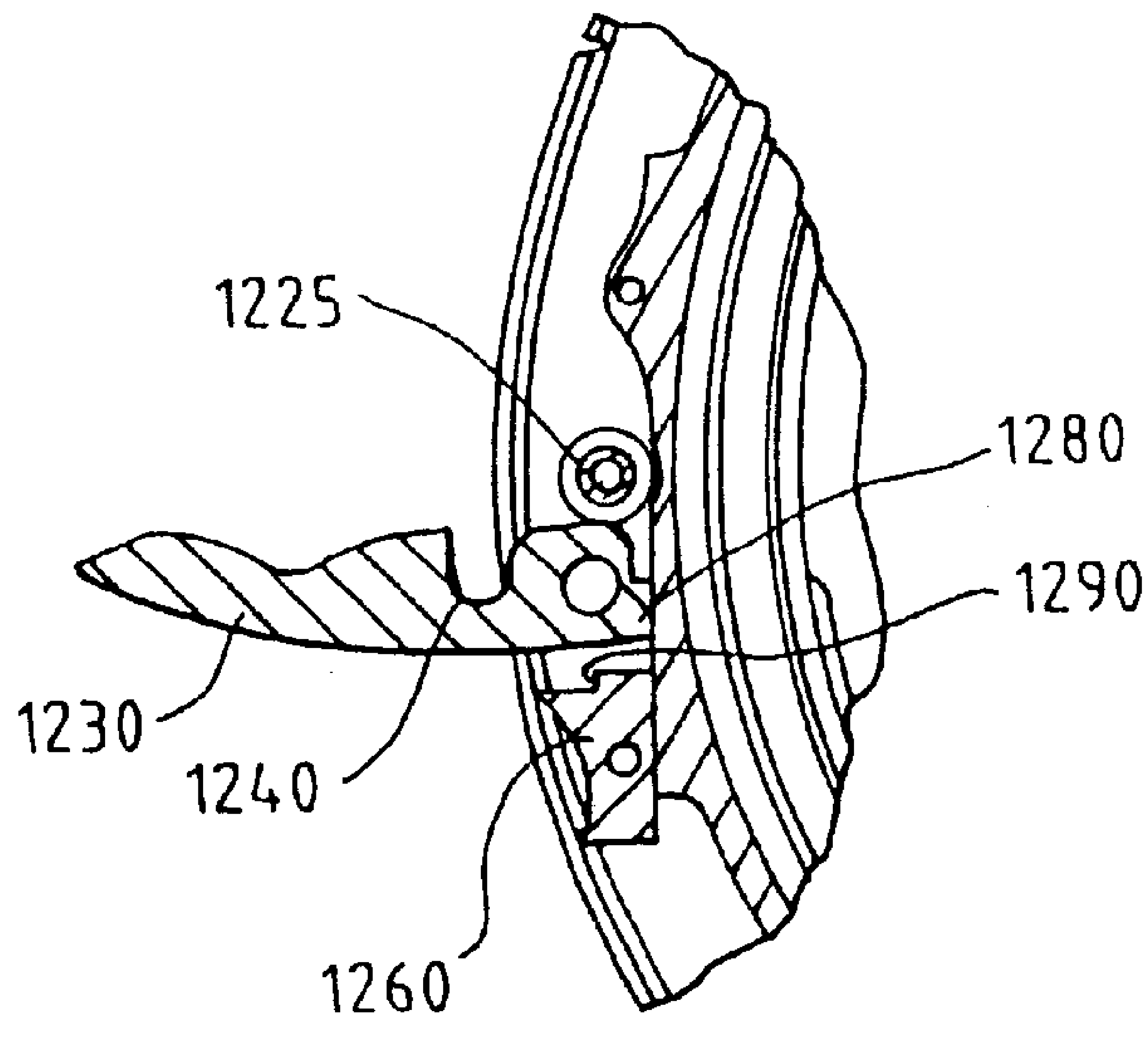


FIG. 19C

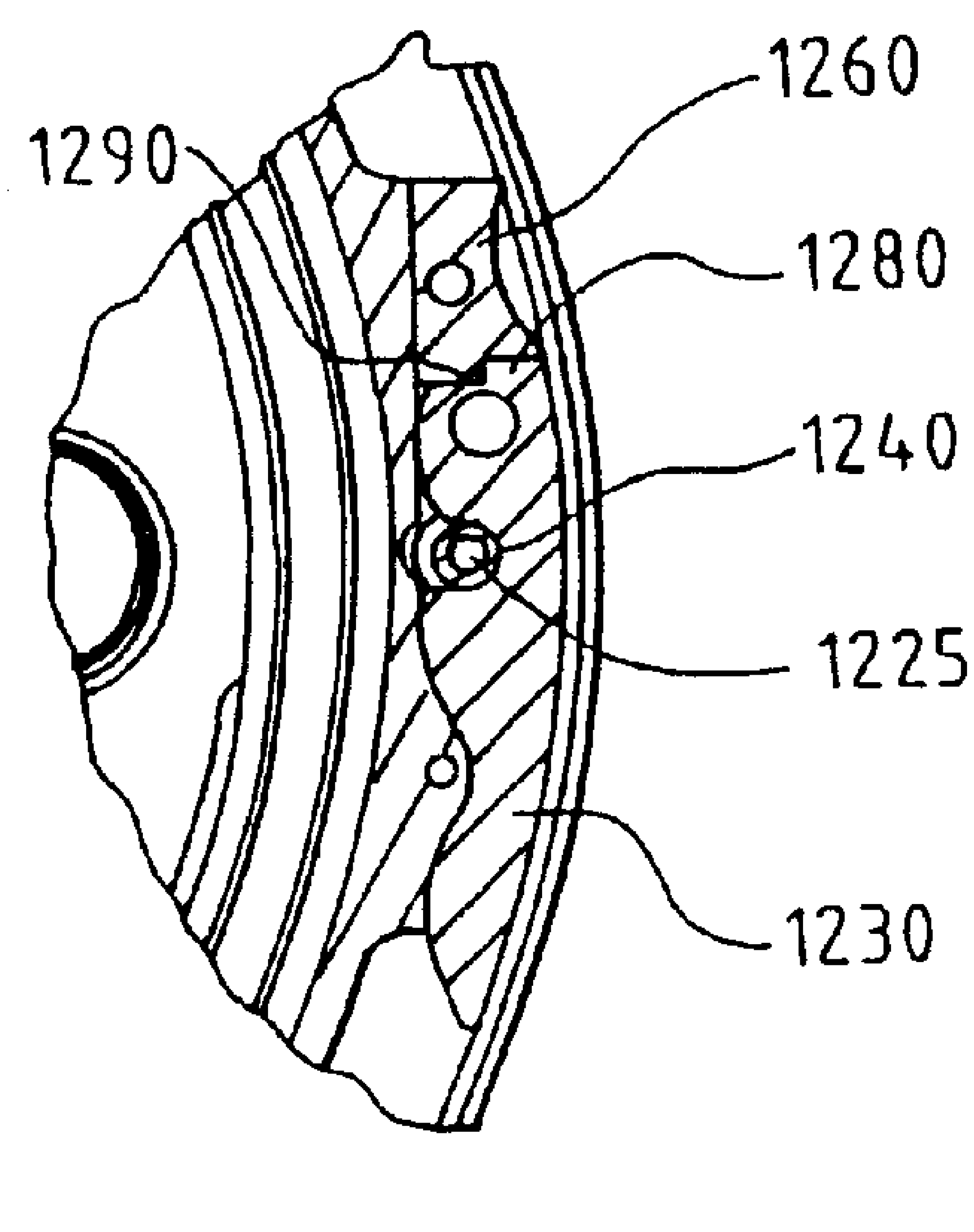


FIG. 20A

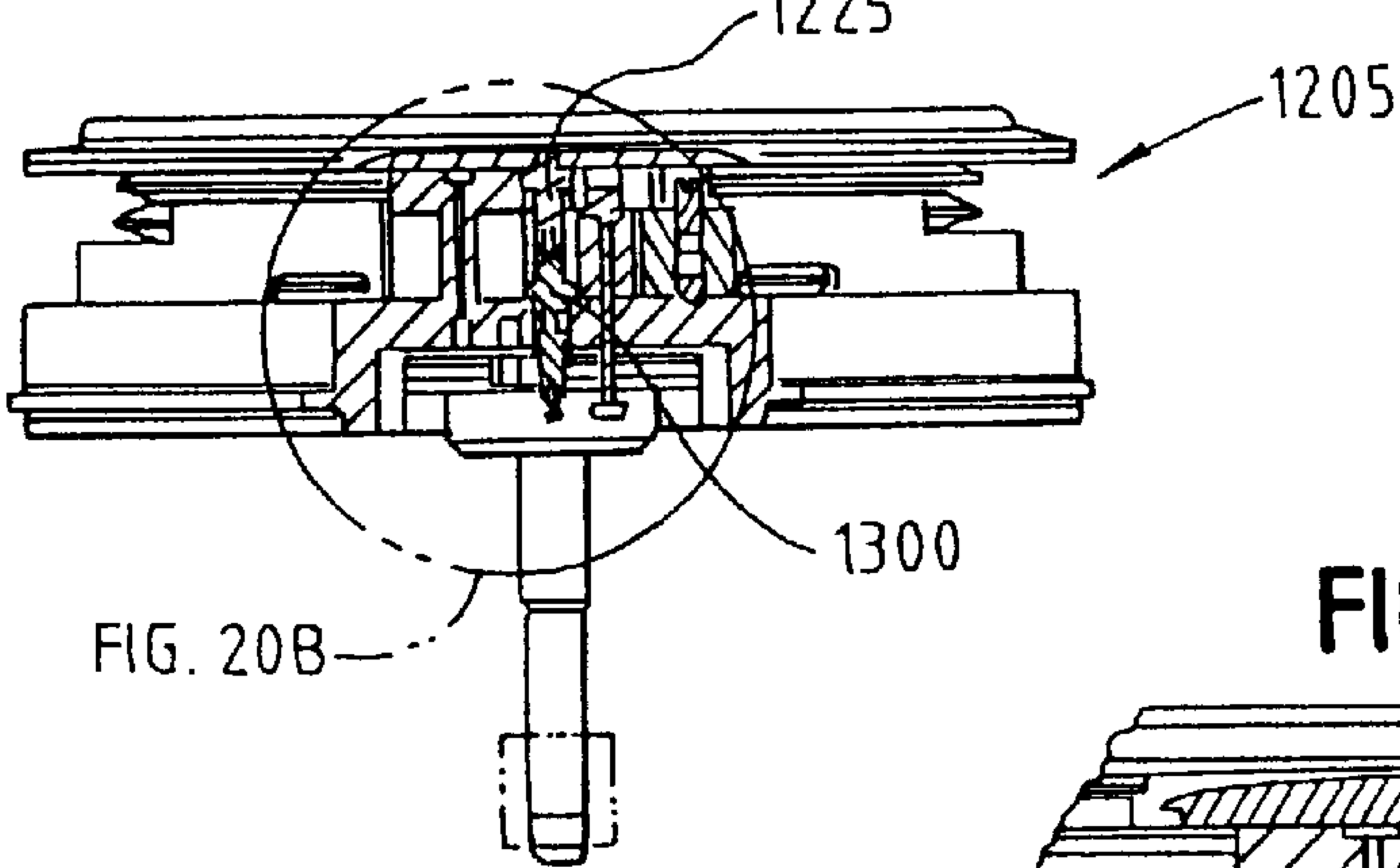


FIG. 20B

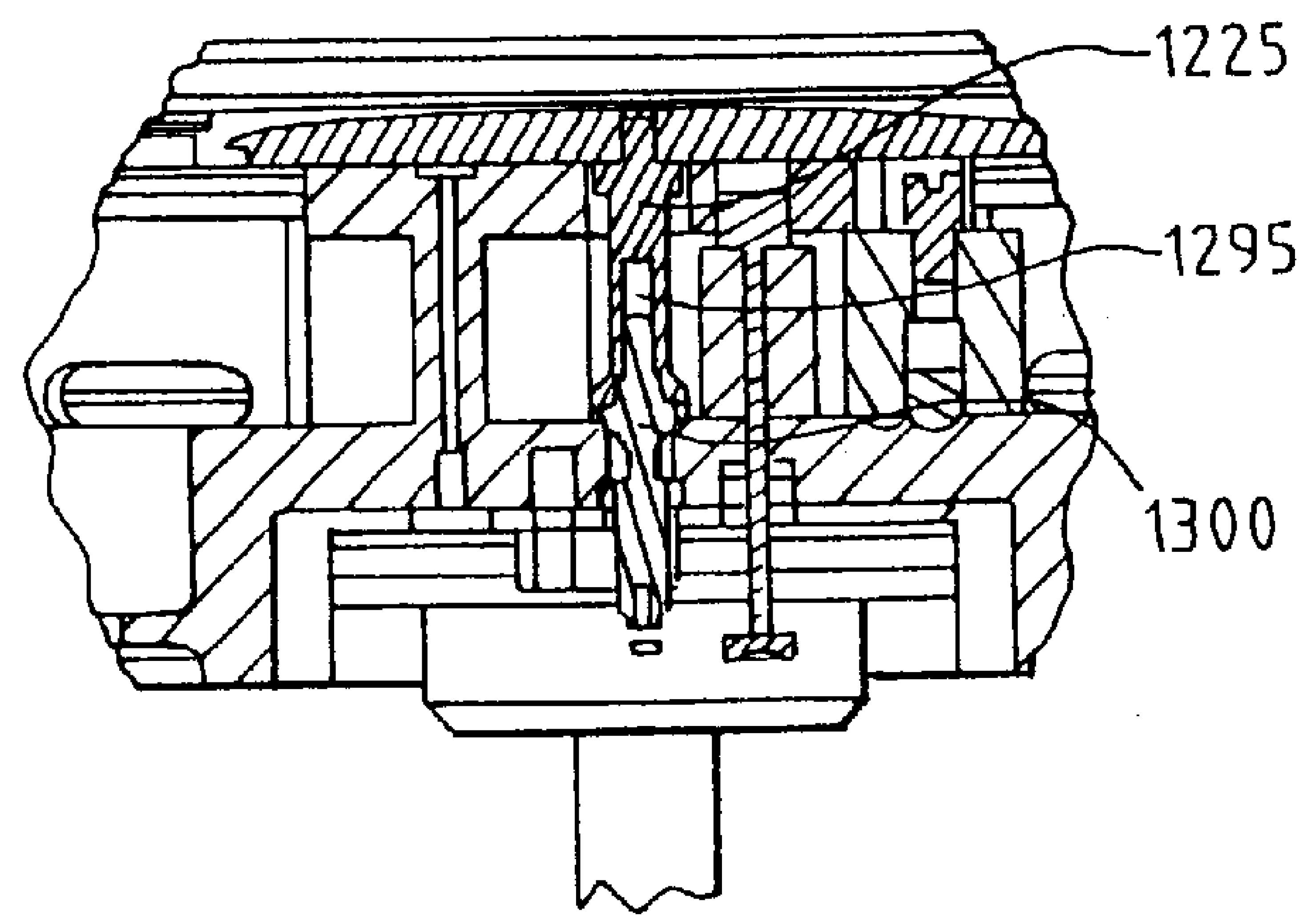


FIG. 20C

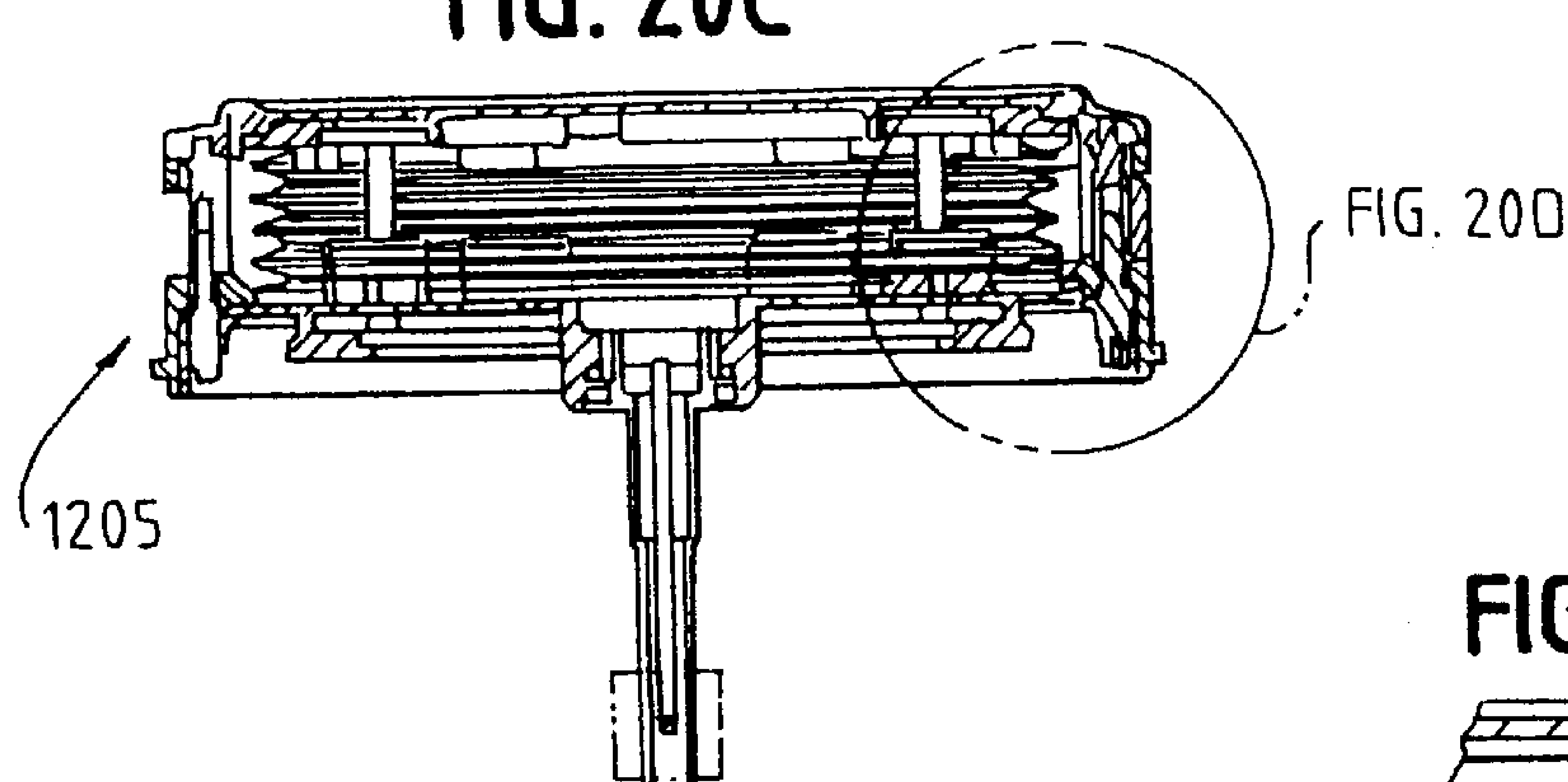
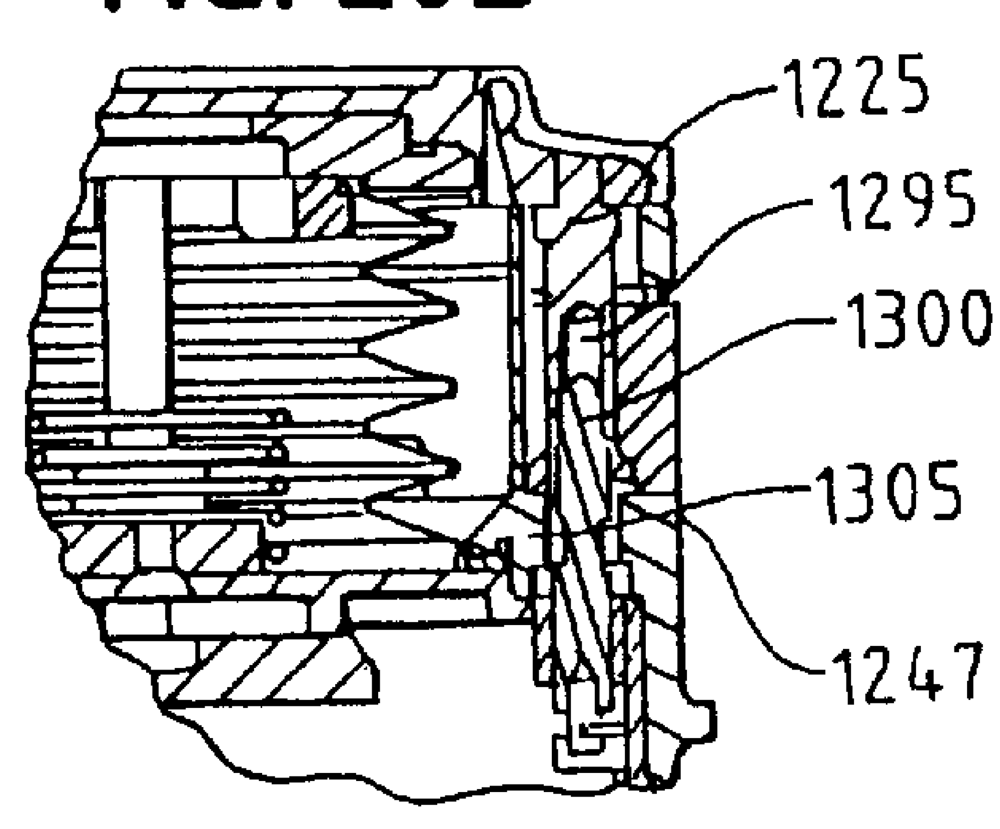


FIG. 20D



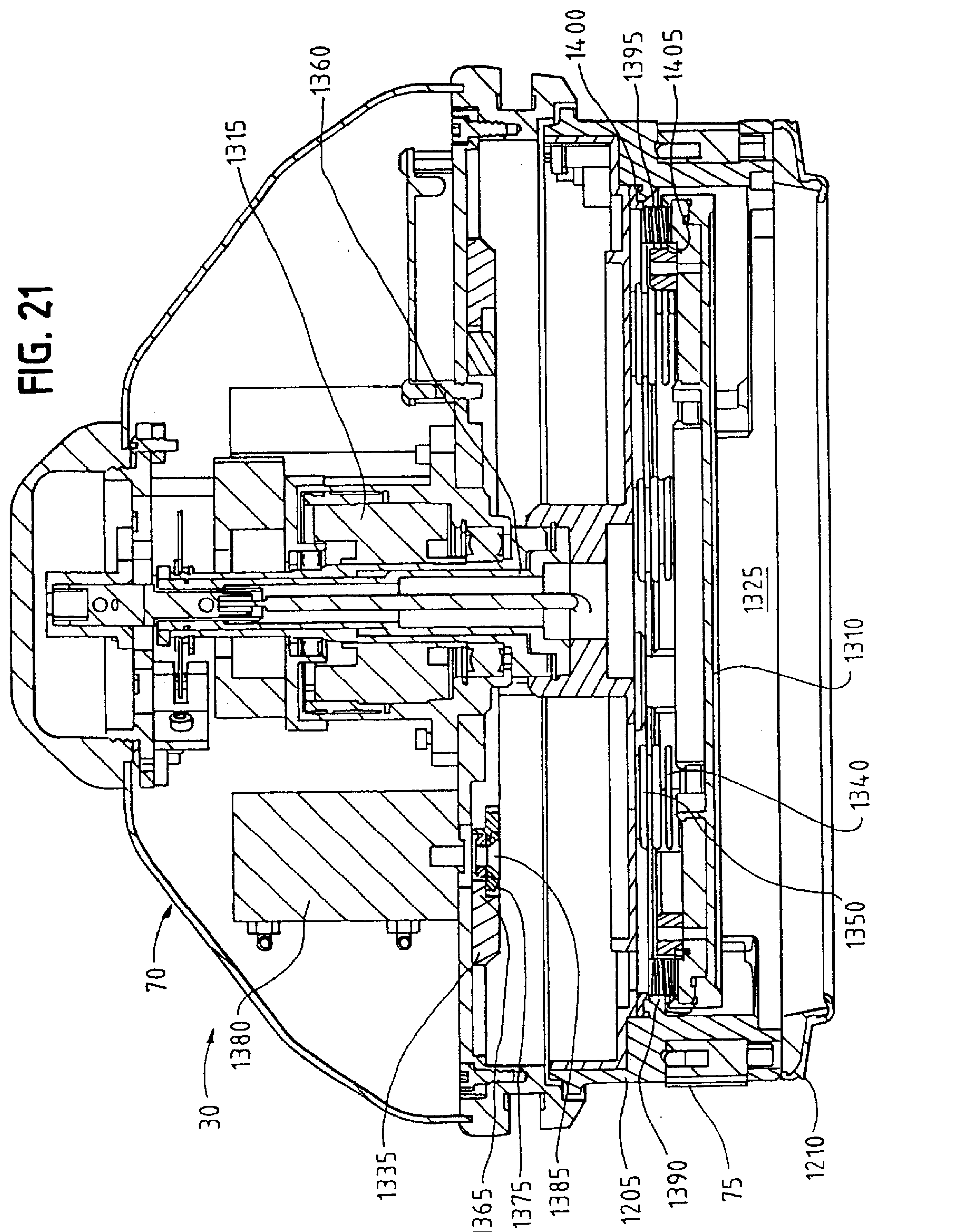

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FIG. 21

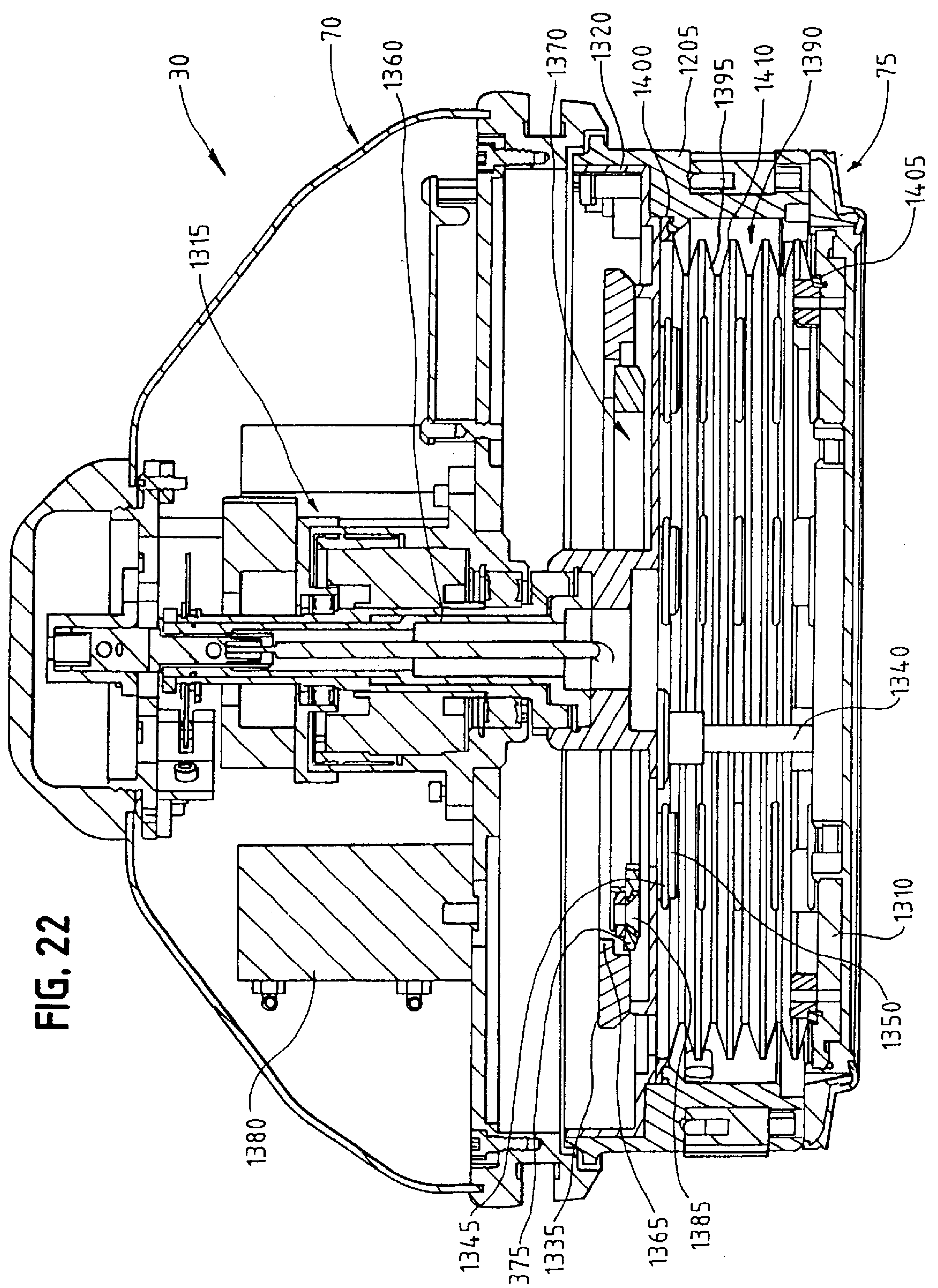
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FIG. 22

FIG. 23

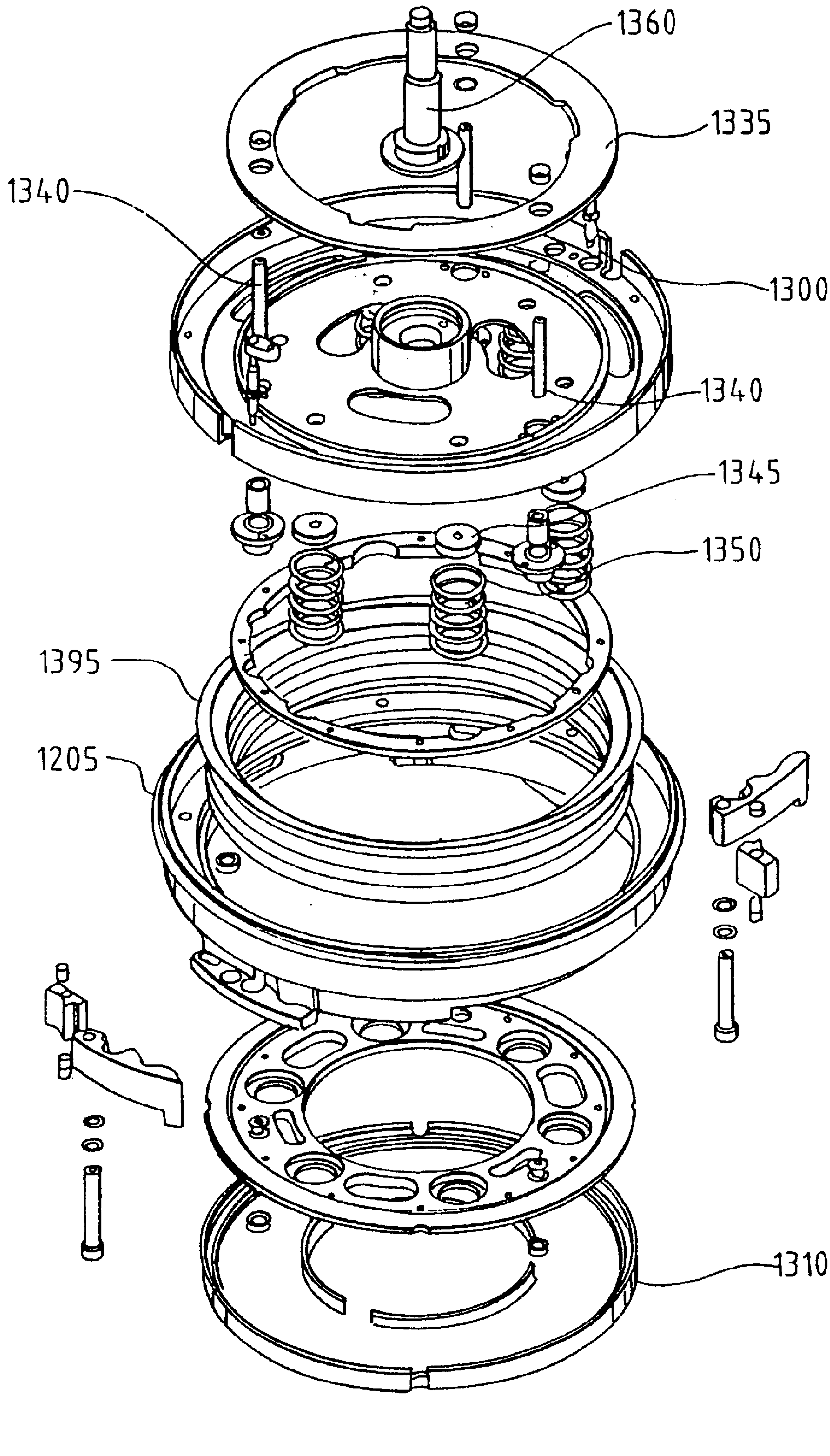


FIG. 24

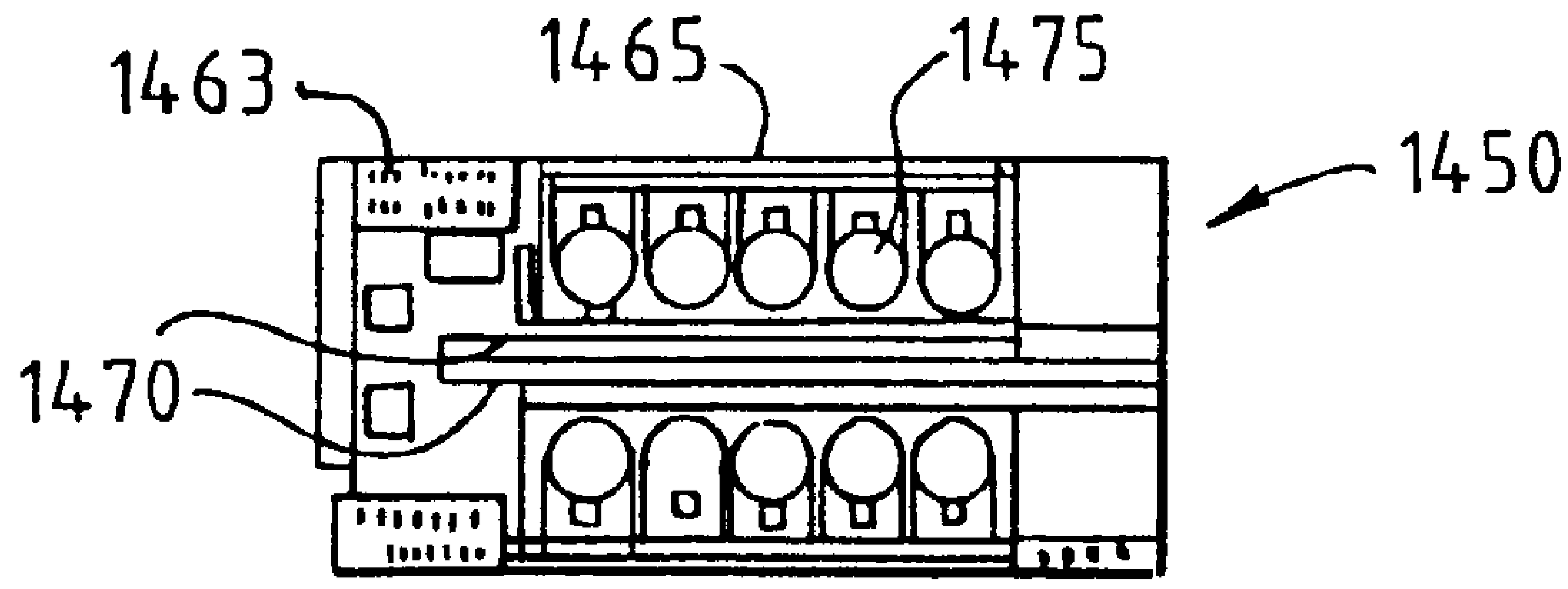


FIG. 25

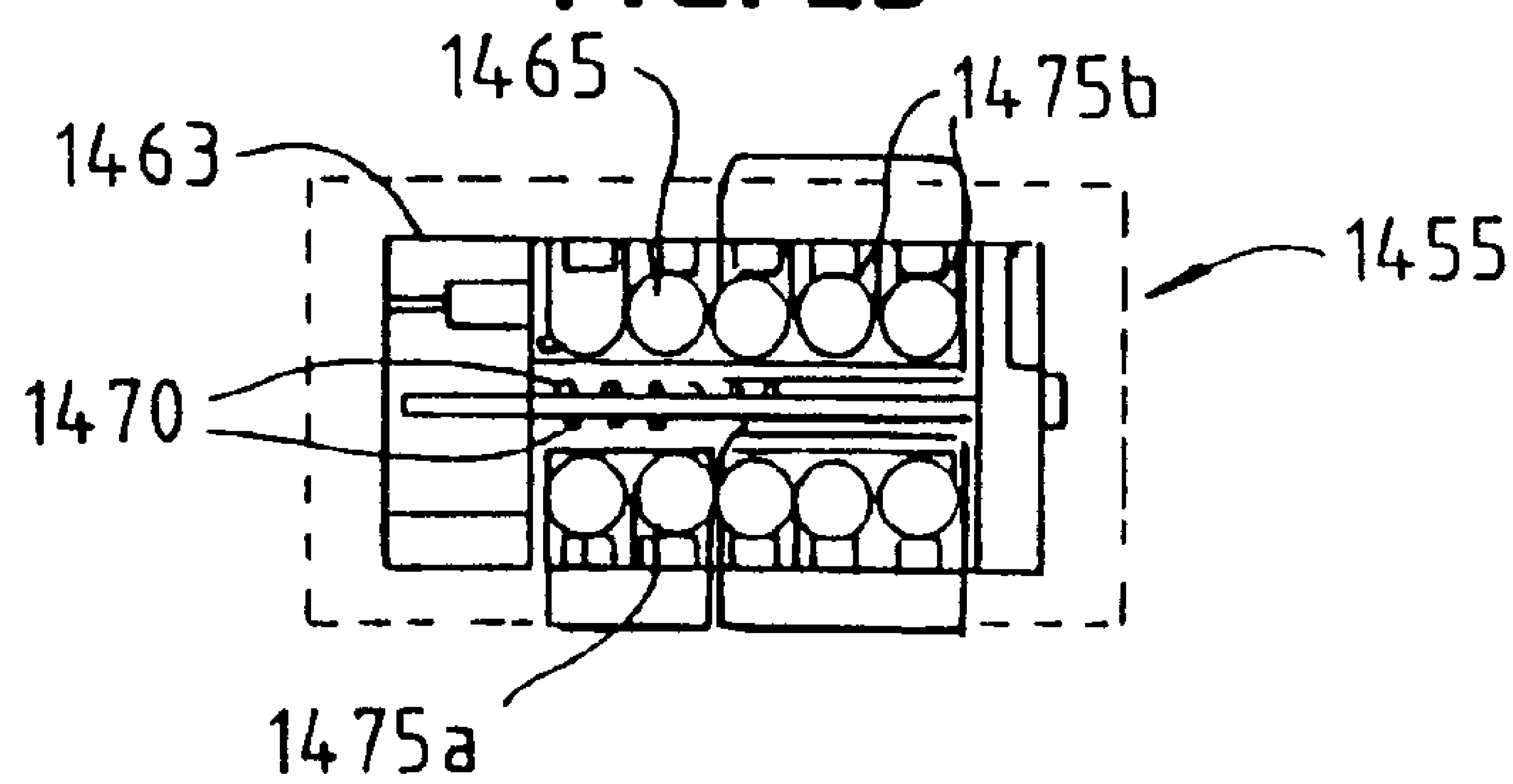
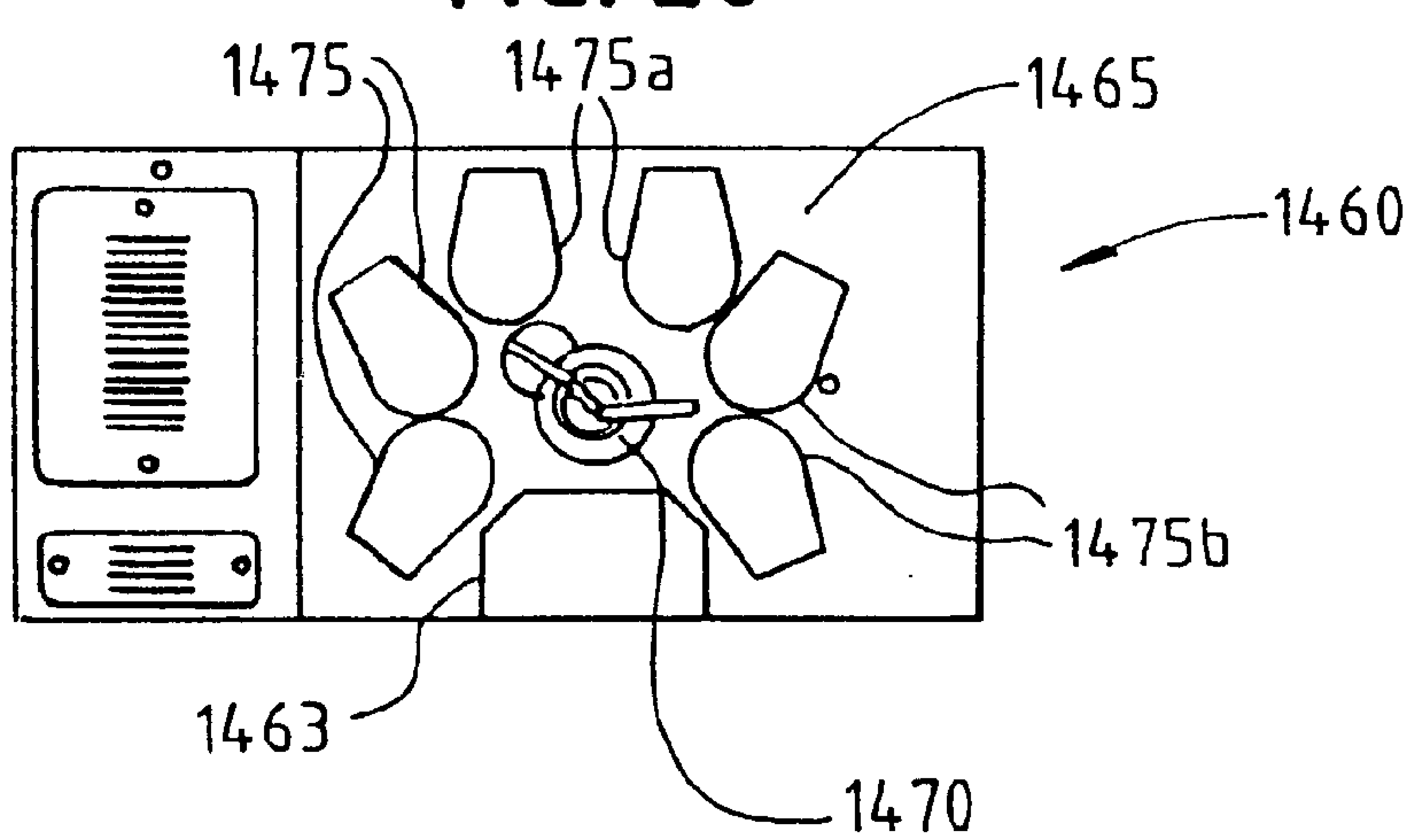


FIG. 26



APPARATUS FOR HIGH DEPOSITION RATE SOLDER ELECTROPLATING ON A MICROELECTRONIC WORKPIECE

CROSS-REFERENCE TO RELATED APPLICATION

This is a continuation application of International PCT Patent Application No. PCT/US99/15850, designating the US, filed Jul. 12, 1999, entitled METHOD, CHEMISTRY, AND APPARATUS FOR HIGH DEPOSITION RATE SOLDER ELECTROPLATING ON A MICROELECTRONIC WORKPIECE, which claims priority from U.S. patent application Ser. No. 60/114,450, filed Dec. 31, 1998.

BACKGROUND OF THE INVENTION

Soldering has been a familiar technique for forming electrical and/or mechanical connections between metal surfaces and is the technique of choice for many applications in the electronics industry. Many soldering techniques have therefore been developed for applying solder to surfaces or interfaces between metals to extend soldering techniques to many diverse applications.

In the electronics industry, in particular, the trend toward smaller sizes of components and higher integration densities of integrated circuits has necessitated techniques for application of solder to extremely small areas and in carefully controlled volumes to avoid solder bridging between conductors.

High performance microelectronic devices often use solder balls or solder bumps for electrical interconnection to other microelectronic devices. For example, a very large scale integration (VLSI) chip may be electrically connected to a circuit board or other next level packaging substrate using solder balls or solder bumps. This connection technology is also referred to as "Controlled Collapse Chip Connection-C4" or "flip-chip" technology, and is often referred to as solder bumps.

In accordance with one type of solder bump technology developed by IBM, the solder bumps are formed by evaporation through openings in a shadow mask which is clamped to an integrated circuit wafer. For example, U.S. Pat. No. 5,234,149 entitled "Debondable Metallic Bonding Method" to Katz et al. discloses an electronic device with chip wiring terminals and metallization layers. The wiring terminals are typically primarily aluminum, and the metallization layers may include a titanium or chromium localized adhesive layer, a co-deposited localized chromium copper layer, a localized wettable copper layer, and a localized gold or tin capping layer. An evaporated localized lead-tin solder layer is located on the capping layer.

Solder bump technology based on an electroplating method has also been actively pursued. In this method, an "under bump metallurgy" (UBM) layer is deposited on a microelectronic substrate having contact pads thereon, typically by evaporation or sputtering. A continuous under bump metallurgy layer is typically provided on the pads and on the substrate between the pads, in order to allow current flow during solder plating.

An example of an electroplating method with an under bump metallurgy layer is disclosed in U.S. Pat. No. 5,162,257 entitled "Solder Bump Fabrication Method" to Yung. In this patent, the under bump metallurgy layer contains a chromium layer adjacent the substrate and pads, a top copper layer which acts as a solderable metal, and a phased chromium/copper layer between the chromium and copper layers. The base of the solder bump is preserved by converting the under bump metallurgy layer between the solder bump and contact pad into an intermetallic of the solder and the solderable component of the under bump metallurgy layer. Multiple etch cycles may, however, be needed to remove the phased chromium/copper layer and the bottom chromium layer. Even with multiple etch cycles, the under bump metallurgy layer may be difficult to remove completely, creating the risk of electrical shorts between solder bumps. U.S. Pat. No. 5,767,010, titled "Solder Bump Fabrication Methods and Structure Including a Titanium Barrier Layer", issued Jun. 16, 1998, purports to address this problem.

Several technical problems are typically associated with electroplating of tin/lead solder on semiconductor wafers and other microelectronic workpieces. One problem relates to the relatively low rate at which deposition of the solder takes place. Generally, the upper deposition rate for selectively depositing solder on the surface of a microelectronic workpiece is about 1 micron/minute. Attempts to significantly increase the deposition rate have heretofore proven unsuccessful. Most such attempts are hindered by the fact that a significant amount of gas evolves during the electroplating process, particularly when traditional inert anodes are employed. The resulting gas bubbles impair the proper formation of the solder bumps and other structures formed from the solder deposit. Additionally, removal of the evolved gases can be problematic. The microelectronic fabrication industry thus has been forced to accept low deposition rate solder processes and equipment.

Several technical problems must be overcome in designing reactors used in the electroplating of semiconductor wafers. Utilization of a small number of discrete electrical contacts (e.g., 6 contacts) with the seed layer about the perimeter of the wafer ordinarily produces higher current densities near the contact points than at other portions of the wafer. This non-uniform distribution of current across the wafer, in turn, causes non-uniform deposition of the plated solder material. Current thieving, effected by the provision of electrically-conductive elements other than those which contact the seed layer, can be employed near the wafer contacts to minimize such non-uniformiity. But such thieving techniques add to the complexity of electroplating equipment, and increase maintenance requirements.

Another problem with electroplating of wafers concerns efforts to prevent the electric contacts themselves from being plated during the electroplating process. Any solder plated to the electrical contacts must be removed to prevent changing contact performance. While it is possible to provide sealing mechanisms for discrete electrical contacts, such arrangements typically cover a significant area of the wafer surface, and can add complexity to the electrical contact design.

In addressing a further problem, it is sometimes desirable to prevent electroplating on the exposed barrier layer near the edge of the semiconductor wafer. Electroplated solder may not adhere well to the exposed barrier layer material, and is therefore prone to peeling off in subsequent wafer processing steps. Further, solder that is electroplated onto the barrier layer within the reactor may flake off during the electroplating process thereby adding particulate contaminants to the electroplating bath. Such contaminants can adversely affect the overall electroplating process.

The specific solder to be electroplated can also complicate the electroplating process. For example, electroplating of solder may require use of a seed layer having a relatively high electrical resistance. As a consequence, use of the typical plurality of electrical wafer contacts (for example, six. (6) discrete contacts) may not provide adequate uniformity of the plated metal layer on the wafer.

Beyond the contact related problems discussed above, there are also other problems associated with electroplating reactors for solder plating. As device sizes decrease, the need for tighter control over the processing environment increases. This includes control over the contaminants that affect the electroplating process. The moving components of the reactor, which tend to generate such contaminants, should therefore be subject to strict isolation requirements.

Still further, existing electroplating reactors are often difficult to maintain and/or reconfigure for different electroplating processes. Such difficulties must be overcome if an electroplating reactor design is to be accepted for large-scale manufacturing.

SUMMARY OF THE INVENTIONS

The present invention is accordingly directed to an improved electroplating method, chemistry, and apparatus for selectively depositing tin/lead solder bumps and other structures at a high deposition rate pursuant to manufacturing a microelectronic device from a workpiece, such as a semiconductor wafer. An apparatus for plating solder on a microelectronic workpiece in accordance with one aspect of the present invention comprises a reactor chamber containing an electroplating solution having free ions of tin and lead for plating onto the workpiece. A chemical delivery system is used to deliver the electroplating solution to the reactor chamber at a high flow rate. A workpiece support is used that includes a contact assembly for providing electroplating power to a surface at a side of the workpiece that is to be plated. The contact contacts the workpiece at a large plurality of discrete contact points that isolated from exposure to the electroplating solution. An anode, preferably a consumable anode, is spaced from the workpiece support within the reaction chamber and is in contact with the electroplating solution. In accordance with one embodiment the electroplating solution comprises a concentration of a lead compound, a concentration of a tin compound, water and methane sulfonic acid.

In accordance with one aspect of the present invention, the contact assembly comprises a plurality of contacts disposed to contact a peripheral edge of the surface of the workpiece. The plurality of contacts execute a wiping action against the surface of the workpiece as the workpiece is brought into engagement therewith. Further, the contact assembly includes a barrier disposed interior of the plurality of contacts that includes a member disposed to engage the surface of the workpiece to effectively isolate the plurality of contacts from the electroplating solution.

BRIEF DESCRIPTION OF THE DRAWINGS

FIG. **1** is a cross-sectional view through an electroplating reactor that is constructed in accordance with various teachings of the present invention.

FIG. **2** illustrates a specific construction of one embodiment of a reactor bowl suitable for use in the assembly illustrated in FIG. **1**.

FIG. **3** illustrates one embodiment of a reactor head, comprised of a stationary assembly and a rotor assembly that is suitable for use in the assembly illustrated in FIG. **1**.

FIGS. **4**–**10** illustrate one embodiment of a contact assembly using flexure contacts that is suitable for use in the reactor assembly illustrated in FIG. **1**.

FIGS. **11**A and B and **12** illustrate two different embodiments of a "Belleville ring" contact structure.

FIGS. **13**–**15** illustrate one embodiment of a contact assembly using a "Belleville ring" contact structure, such as one of those illustrated in FIGS. **11**–**12**, that is suitable for use in the reactor assembly illustrated in FIG. **1**.

FIGS. **16**–**17**, **18**A–B, **19**A–C, and **20**A–D illustrate various aspects of one embodiment of a quick-attach mechanism.

FIG. **21** is a cross-sectional view of the reactor head illustrating the disposition of the reactor head in a condition in which it may accept a workpiece.

FIG. **22** is a cross-sectional view of the reactor head illustrating the disposition of the reactor head in a condition in which it is ready to present the workpiece to the reactor bowl.

FIG. **23** illustrates an exploded view one embodiment of the rotor assembly.

FIGS. **24**–**26** are top plan views of integrated processing tools that may incorporate electroless plating reactors and electroplating reactors in combination.

DETAILED DESCRIPTION OF THE INVENTIONS

BASIC SOLDER ELECTROPLATING REACTOR COMPONENTS

With reference to FIGS. **1**–**3**, there is shown a reactor assembly **20** for high deposition rate electroplating of solder on a microelectronic workpiece, such as a semiconductor wafer **25**. Generally stated, the reactor assembly **20** is comprised of a reactor head **30** and a corresponding reactor bowl **35**. This type of reactor assembly is particularly suited for effecting electroplating of semiconductor wafers or like workpieces, in which an electrically conductive, thin-film seed layer of the wafer is electroplated with a blanket or patterned metallic layer, such as a layer of solder bumps.

The specific construction of one embodiment of a reactor bowl **35** suitable for use in the reactor assembly **20** is illustrated in FIG. **2**. The electroplating reactor bowl **35** is that portion of the reactor assembly **20** that contains electroplating solution, and that directs the solution at a high flow rate against a generally downwardly facing surface of an associated workpiece **25** to be plated. To this end, electroplating solution is circulated through the reactor bowl **35**. Attendant to solution circulation, the solution flows from the reactor bowl **35**, over the weir-like periphery of the bowl, into a lower overflow chamber **40** of the reactor assembly **20**. Solution is drawn from the overflow chamber typically for re-circulation through the reactor.

The temperature of electroplating solution is monitored and maintained by a temperature sensor and heater, respectively. The sensor and heater are disposed in the circulation path of the electroplating solution. These components preferably maintain the temperature of the electroplating solution in a temperature range between 20° C. and 50° C. Even more preferably, these components maintain the temperature of the electroplating solution at about 30° C. +/5° C. As will be explained in connection with the preferred electroplating process, the preferred electroplating solution exhibits optimal deposition properties within this latter temperature range. The reactor bowl **35** includes a riser tube **45**, within which an inlet conduit **50** is positioned for introduction of electroplating solution into the interior portion of the reactor bowl **35**. The inlet conduit **50** is preferably conductive and makes electrical contact with and supports an electroplating anode **55**. Unlike the inert anodes used in conventional electroplating of solder to a surface of a microelectronic workpiece, anode **55** is a consumable anode formed from tin and/or lead whereby tin and lead ions of the anode are transported by the electroplating solution to the electrically-conductive surface of the workpiece, which functions as a cathode. Preferably, the consumable anode **55** has a tin/lead composition that directly corresponds to the tin/lead composition required for the solder deposit. As such, an anode used in an electroplating system for depositing high lead content solder should have a corresponding high lead-tin ratio. Similarly, an anode used in an electroplating system for depositing eutectic solder should have a corresponding low lead-tin ratio. As illustrated, the anode **55** may be provided with an anode shield **60**.

Electroplating solution flows at a high flow rate (i.e., 5 g/m) from the inlet conduit **50** through openings at the upper portion thereof. From there, the solution flows about the anode **55**, and through an optional diffusion plate **65** positioned in operative association with and between the cathode (workpiece) and the anode.

The reactor head **30** of the electroplating reactor **20** is preferably comprised of a stationary assembly **70** and a rotor assembly **75**, diagrammatically illustrated in FIG. **3**. Rotor assembly **75** is configured to receive and carry an associated wafer **25** or like workpiece, position the wafer in a process-side down orientation within reactor bowl **35**, and to rotate or spin the workpiece while joining its electrically-conductive surface in the plating circuit of the reactor assembly **20**. The reactor head **30** is typically mounted on a lift/rotate apparatus **80**, which is configured to rotate the reactor head **30** from an upwardly-facing disposition, in which it receives the wafer to be plated, to a downwardly facing disposition, in which the surface of the wafer to be plated is positioned downwardly in reactor bowl **35**, generally in confronting relationship to diffusion plate **65**. A robotic arm **415**, including an end effector, is typically employed for placing the wafer **25** in position on the rotor assembly **75**, and for removing the plated wafer from the rotor assembly.

ELECTROPLATING SOLUTION

The preferred electroplating solution is comprised of methane sulfonic acid, a source of lead ions, a source of tin ions, one or more organic additives, and deionized water. Complementary sets of materials that are specifically designed for electroplating a tin/lead solder composition are available from LeaRonal, Enthone-OMI, Lucent, and Technic.

The chemical salts used for the generation of lead and tin ions are provided in a ratio that corresponds, although not necessarily directly, to the lead-to-tin ratio of the required solder deposit. Two solder deposit compositions that are typically used for attachment of semiconductor integrated circuits using flip-chip technology are eutectic solder (63% Sn, 37% Pb) and high lead solder (95% to 97% Pb, with the balance being Sn). Electroplating solutions used for electroplating a eutectic solder thus have a higher concentration of tin than of lead. Similarly, electroplating solutions used for electroplating high lead solder have a higher concentration of lead than of tin. Although there is a correspondence between the general ratios of the lead and tin used for depositing a given solder composition, this correspondence is not necessarily one-to-one. This is due to the fact that the efficiencies associated with plating lead from the solution may be significantly lower than the efficiencies associated with plating tin from the solution (i.e., it is more difficult to plate lead from the solution than it is to plate tin from the solution).

The overall combined concentration of the metal ions of lead and tin utilized in the electroplating solution is dependent on the requisite rate of deposition, the particular compositions of the lead and tin concentrates (which often differs between manufacturers), the composition of the consumable anode **55**, the operating temperature of the solution, cathode current density, and the desired composition of the solder deposit. The combined metal concentration should be chosen so that it is large enough to meet the requisite deposition rate while not so large as to evolve a significant amount of gas by-products that interfere with the plating process or otherwise result in unsatisfactory solder deposits. For a high rate plating of high lead content solder, the combined metal concentration is preferably between 55 g/liter and 205 g/liter. For a high rate plating of eutectic solder, lower combined metal concentrations may be used in view of the lower lead composition of the eutectic solder deposit.

The present inventors have found that high rate plating of about 4 microns/minute may be achieved with the following electroplating solutions, in which the particular additives are provided by the identified manufacturer. The compositions for these electroplating solutions are set forth in the following tables, and are directed to high rate plating of high lead content solder (95/5). It is believed that plating rates as high as 8 microns/minute are possible using these basic solutions and the reactor described above.

TABLE 1

MANUFACTURER/BRAND-NAME	LeaRonal Solderon SC ™
METHANE SULFONIC ACID	120–180 g/liter - preferably, 150 g/liter
LEAD CONCENTRATION	50–100 g/liter - preferably, 75 g/liter
TIN CONCENTRATION	3–7 g/liter - preferably, 5 g/liter
ORGANIC ADDITIVE	20%–30% by volume
WATER	50%–60% by volume

TABLE 2

MANUFACTURER/BRAND-NAME	LeaRonal MHS-L ™
METHANE SULFONIC ACID	120–180 g/liter
LEAD CONCENTRATION	130–170 g/liter
TIN CONCENTRATION	15–35 g/liter
ORGANIC ADDITIVE	20%–30% by volume
WATER	50%–60% by volume

TABLE 3

MANUFACTURER/BRAND-NAME	Lucent
METHANE SULFONIC ACID	20%–30% by volume
LEAD CONCENTRATE CONCENTRATION	8%–10% by volume
TIN CONCENTRATE CONCENTRATION	3%–5% by volume
ORGANIC ADDITIVE	6%–8% by volume
WATER	60%–70% by volume

TABLE 4

MANUFACTURER/BRAND-NAME	Technic
TECHNI ACID NF	15% by volume
TECHNI LEAD NF 500 CONCENTRATION	5% by volume
TECHNI TIN NF 300 CONCENTRATION	13.3% by volume
TECHNI NF 820 HS MAKEUP	5% by volume
TECHNI NF 820 HS SECONDARY ADDITIVE	0.3% by volume
WATER	balance of remaining volume %

The foregoing solution compositions can also be adjusted with respect to the lead and tin concentrations to optimize those solutions for depositing eutectic solder. For example, the solution compositions set forth in TABLE 5 below may be used to deposit eutectic solder at a high plating rate of about 2 microns/minute with excellent results. It is expected that a solution in which the tin and lead additive concentrations are doubled will produce a eutectic solder deposit at a high plating rate of about 4 microns/minute.

TABLE 5

MANUFACTURER/BRAND-NAME	LeaRonal Solderon SC ™
METHANE SULFONIC ACID	120–180 g/liter - preferably, 150 g/liter
LEAD CONCENTRATION	about 10 g/liter
TIN CONCENTRATION	about 23.5 g/liter
ORGANIC ADDITIVE	20%–30% by volume
WATER	50%–60% by volume

EXEMPLARY PROCESS

The reactor system and electroplating solutions described above can be used to implement a process for depositing lead-tin solder at a high rate of deposition in excess of about 2 microns/minute and potentially as high as 8 microns/minute. An exemplary process sequence preferably includes the following processing steps:

1. Pre-wet the substrate material using deionized water or acid and/or a surfactant to eliminate the dry plating surface (about 30 seconds) (the pre-wet solution may also include an amount of MSA and be heated to the same temperature at which electroplating will occur);
2. Adjust and/or program the electroplating system for the following processing parameters: electroplating flow set-point at nominal 5 gpm (or other high flow rate of comparable magnitude), electroplating bath temperature about 20° C.–50° C. (preferably, about 30° C.), rotate workpiece at a rotation rate between about 1 and 100 rpm (preferably, about 20 rpm), change the direction of the rotation at intervals between about 5 and 60 seconds;
3. Bring the surface of the workpiece that is to be plated into contact with the electroplating solution without application of electroplating power thereby inducing an acid etch of the substrate (about 30 seconds);
4. Apply electroplating power at a current set-point that is between about 50 and 200 milliamps/cm^2(time duration dependent on desired vertical plate height or bump volume);
5. Halt electrolysis;
6. Disengage workpiece from electroplating solution;
7. Spin the workpiece at a high spin rate (i.e., above about 200 rpm) to remove excess electroplating solution;
8. Rinse the workpiece in a spray of deionized water (about 2 min.) and spin dry at a high rotation rate.

Other processing sequences may also be used to provide high-quality solder deposits that are deposited at a high deposition rate, the foregoing processing steps and sequence being illustrative. As will be set forth in further detail below, the foregoing processing steps and sequence may be implemented in a single fabrication tool having a plurality of similar processing stations and a programmable robot that transfers the workpieces between such stations.

There are a number of enhancements that may be made to the reactor assembly 20 described above that facilitate uniformity of the solder deposits over the face of the workpiece. For example, the reactor assembly 20 may use a contact assembly that reduces non-uniformities in the deposit that occur proximate the discrete contacts that are used to provide plating power to the surface at the perimeter of the workpiece. Additionally, other enhancements to the reactor assembly 20 may be added to facilitate routine service and/or configurability of the system.

IMPROVED CONTACT ASSEMBLIES FOR ELECTROPLATING SOLDER

The manner in which the electroplating power is supplied to the wafer at the peripheral edge thereof is very important to the overall film quality of the deposited solder. Some of the more desirable characteristics of a contact assembly used to provide such electroplating power include, for example, the following:

- uniform distribution of electroplating power about the periphery of the wafer to maximize the uniformity of the deposited film;
- consistent contact characteristics to insure wafer-to-wafer uniformity;
- minimal intrusion of the contact assembly on the wafer periphery to maximize the available area for device production; and
- minimal plating on the barrier layer about the wafer periphery to inhibit peeling and/or flaking.

To meet one or more of the foregoing characteristics, reactor **20** preferably employs a ring contact assembly **85** that provides either a continuous electrical contact or a high number of discrete electrical contacts with the wafer **25**. By providing a more continuous contact with the outer peripheral edges of the semiconductor wafer **25**, in this case around the outer circumference of the semiconductor wafer, a more uniform current is supplied to the semiconductor wafer **25** that promotes more uniform current densities. The more uniform current densities enhance uniformity in the depth of the deposited material.

Contact assembly **85**, in accordance with a preferred embodiment, includes contact members that provide minimal intrusion about the wafer periphery while concurrently providing consistent contact with the seed layer. Contact with the seed layer is enhanced by using a contact member structure that provides a wiping action against the seed layer as the wafer is brought into engagement with the contact assembly. This wiping action assists in removing any oxides at the seed layer surface thereby enhancing the electrical contact between the contact structure and the seed layer. As a result, uniformity of the current densities about the wafer periphery are increased and the resulting film is more uniform. Further, such consistency in the electrical contact facilitates greater consistency in the electroplating process from wafer-to-wafer thereby increasing wafer-to-wafer uniformity.

Contact assembly **85**, as will be set forth in further detail below, also preferably includes one or more structures that provide a barrier, individually or in cooperation with other structures, that separates the contact/contacts, the peripheral edge portions and backside of the semiconductor wafer **25** from the plating solution. This prevents the plating of metal onto the individual contacts and, further, assists in preventing any exposed portions of the barrier layer near the edge of the semiconductor wafer **25** from being exposed to the electroplating environment. As a result, plating of the barrier layer and the appertaining potential for contamination due to flaking of any loosely adhered electroplated material is substantially limited.

RING CONTACT ASSEMBLIES USING FLEXURE CONTACTS

One embodiment of a contact assembly suitable for use in the assembly **20** is shown generally at **85** of FIGS. **4**–**10**. The contact assembly **85** forms part of the rotor assembly **75** and provides electrical contact between the semiconductor wafer **25** and a source of electroplating power. In the illustrated embodiment, electrical contact between the semiconductor wafer **25** and the contact assembly **85** occurs at a large plurality of discrete flexure contacts **90** that are effectively separated from the electroplating environment interior of the reactor bowl **35** when the semiconductor wafer **25** is held and supported by the rotor assembly **75**.

The contact assembly **85** may be comprised of several discrete components. With reference to FIG. **4**, when the workpiece that is to be electroplated is a circular semiconductor wafer, the discrete components of the contact assembly **85** join together to form a generally annular component having a bounded central open region **95**. It is within this bounded central open region **95** that the surface of the semiconductor wafer that is to be electroplated is exposed. With particular reference to FIG. **6**, contact assembly **85** includes an outer body member **100**, an annular wedge **105**, a plurality of flexure contacts **90**, a contact mount member **110**, and an interior wafer guide **115**. Preferably, annular wedge **105**, flexure contacts **90**, and contact mount member **110** are formed from platinized titanium while wafer guide **115** and outer body member **100** are formed from a dielectric material that is compatible with the electroplating environment. Annular wedge **105**, flexure contacts **90**, mount member **110**, and wafer guide **115** join together to form a single assembly that is secured together by outer body member **100**.

As shown in FIG. **6**, contact mount member **100** includes a first annular groove **120** disposed about a peripheral portion thereof and a second annular groove **125** disposed radially inward of the first annular groove **120**. The second annular groove **125** opens to a plurality of flexure channels **130** that are equal in number to the number of flexure contacts **90**. As can be seen from FIG. **4**, a total of **36** flexure contacts **90** are employed, each being spaced from one another by an angle of about 10 degrees.

Referring again to FIG. **6**, each flexure contact **90** is comprised of an upstanding portion **135**, a transverse portion **140**, a vertical transition portion **145**, and a wafer contact portion **150**. Similarly, wedge **105** includes an upstanding portion **155** and a transverse portion **160**. Upstanding portion **155** of wedge **105** and upstanding portion **135** of each flexure contact **90** are secured within the first annular groove **120** of the contact mount member **110** at the site of each flexure channel **130**. Self-adjustment of the flexure contacts **90** to their proper position within the overall contact assembly **85** is facilitated by first placing each of the individual flexure contacts **90** in its respective flexure channel **130** so that the upstanding portion **135** is disposed within the first annular groove **120** of the contact mount member **110** while the transition portion **145** and contact portion **150** proceed through the respective flexure channel **130**. The upstanding portion **155** of wedge member **105** is then urged into the first annular groove **120**. To assist in this engagement,.the upper end of upstanding portion **155** is tapered. The combined width of upstanding portion **135** of the flexure contact **90** and upstanding portion **155** of wedge **105** are such that these components are firmly secured with contact mount member **110**.

Transverse portion **160** of wedge **105** extends along a portion of the length of transverse portion **140** of each flexure **90**. In the illustrated embodiment, transverse portion **160** of wedge portion **105** terminates at the edge of the second annular groove **125** of contact mount member **110**. As will be more clear from the description of the flexure contact operation below, the length of transverse portion **160** of wedge **105** can be chosen to provide the desired degree of stiffness of the flexure contacts **90**.

Wafer guide **115** is in the form of an annular ring having a plurality of slots **165** through which contact portions **150** of flexures **90** extend. An annular extension **170** proceeds from the exterior wall of wafer guide **115** and engages a corresponding annular groove **175** disposed in the interior wall of contact mount member **110** to thereby secure the wafer guide **115** with the contact mount member **110**. As illustrated, the wafer guide member **115** has an interior diameter that decreases from the upper portion thereof to the lower portion thereof proximate contact portions **150**. A wafer inserted into contact assembly **85** is thus guided into position with contact portions **150** by a tapered guide wall formed at the interior of wafer guide **115**. Preferably, the portion **180** of wafer guide **115** that extends below annular extension **170** is formed as a thin, compliant wall that resiliently deforms to accommodate wafers having different diameters within the tolerance range of a given wafer size. Further, such resilient deformation accommodates a range of wafer insertion tolerances occurring in the components used to bring the wafer into engagement with the contact portions **150** of the flexures **90**.

Referring to FIG. **6**, outer body member **100** includes an upstanding portion **185**, a transverse portion **190**, a vertical transition portion **195** and a further transverse portion **200** that terminates in an upturned lip **205**. Upstanding portion **185** includes an annular extension **210** that extends radially inward to engage a corresponding annular notch **215** disposed in an exterior wall of contact mount member **110**. A V-shaped notch **220** is formed at a lower portion of the upstanding portion **185** and circumvents the outer periphery thereof. The V-shaped notch **220** allows upstanding portion **185** to resiliently deform during assembly. To this end, upstanding portion **185** resiliently deforms as annular extension **210** slides about the exterior of contact mount member **110** to engage annular notch **215**. Once so engaged, contact mount member **110** is clamped between annular extension **210** and the interior wall of transverse portion **190** of outer body member **100**.

Further transverse portion **200** extends beyond the length of contact portions **150** of the flexure contacts **90** and is dimensioned to resiliently deform as a wafer, such as at **25**, is driven against them. V-shaped notch **220** may be dimensioned and positioned to assist in the resilient deformation of transverse portion **200**. With the wafer **25** in proper engagement with the contact portions **150**, upturned lip **205** engages wafer **25** and assists in providing a barrier between the electroplating solution and the outer peripheral edge and backside of wafer **25**, including the flexure contacts **90**.

As illustrated in FIG. **6**, flexure contacts **90** resiliently deform as the wafer **25** is driven against them. Preferably, contact portions **150** are initially angled upward in the illustrated manner. Thus, as the wafer **25** is urged against contact portions **150**, flexures **90** resiliently deform so that contact portions **150** effectively wipe against surface **230** of wafer **25**. In the illustrated embodiment, contact portions **150** effectively wipe against surface **230** of wafer **25** a horizontal distance designated at **235**. This wiping action assists in removing and/or penetrating any oxides from surface **230** of wafer **25** thereby providing more effective electrical contact between flexure contacts **90** and the seed layer at surface **230** of wafer **25**.

With reference to FIGS. **7** and **8**, contact mount member **110** is provided with one or more ports **240** that may be connected to a source of purging gas, such as a source of nitrogen. As shown in FIG. **8**, purge ports **240** open to second annular groove **125** which, in turn, operates as a manifold to distribute the purging gas to all of the flexure channels **130** as shown in FIG. **6**. The purging gas then proceeds through each of the flexure channels **130** and slots **165** to substantially surround the entire contact portions **150** of flexures **90**. In addition to purging the area surrounding contact portions **150**, the purge gas cooperates with the upturned lip **205** of outer body member **100** to effect a barrier to the electroplating solution. Further circulation of the purge gas is facilitated by an annular channel **250** formed between a portion of the exterior wall of wafer guide **115** and a portion of the interior wall of contact mount member **110**.

As shown in FIGS. **4**, **5** and **10**, contact mount member **110** is provided with one or more threaded apertures **255** that are dimensioned to accommodate a corresponding connection plug **260**. With reference to FIGS. **5** and **10**, connection plugs **260** provide electroplating power to the contact assembly **85** and, preferably, are each formed from platinized titanium. In a preferred form of plugs **260**, each plug **260** includes a body **265** having a centrally disposed bore hole **270**. A first flange **275** is disposed at an upper portion of body **265** and a second flange **280** is disposed at a lower portion of body **265**. A threaded extension **285** proceeds downward from a central portion of flange **280** and secures with threaded bore hole **270**. The lower surface of flange **280** directly abuts an upper surface of contact mount member **110** to increase the integrity of the electrical connection therebetween.

Although flexure contacts **90** are formed as discrete components, they may be joined with one another as an integral assembly. To this end, for example, the upstanding portions **135** of the flexure contacts **90** may be joined to one another by a web of material, such as platinized titanium, that is either formed as a separate piece or is otherwise formed with the flexures from a single piece of material. The web of material may be formed between all of the flexure contacts or between select groups of flexure contacts. For example, a first web of material may be used to join half of the flexure contacts (e.g., 18 flexure contacts in the illustrated embodiment) while a second web of material is used to join a second half of the flexure contacts (e.g., the remaining 18 flexure contacts in the illustrated embodiment). Different groupings are also possible.

BELLEVILLE RING CONTACT ASSEMBLIES

Alternative contact assemblies are illustrated in FIGS. **11**–**15**. In each of these contact assemblies, the contact members are integrated with a corresponding common ring and, when mounted in their corresponding assemblies, are biased upward in the direction in which the wafer or other substrate is received upon the contact members. A top view of one embodiment of such a structure is illustrated in FIG. **11**A while a perspective view thereof is illustrated it FIG. **11**B. As illustrated, a ring contact, shown generally at **610**, is comprised of a common ring portion **630** that joins a plurality of contact members **655**. The common ring portion **630** and the contact members **655**, when mounted in the corresponding assemblies, are similar in appearance to half of a conventional Belleville spring. For this reason, the ring contact **610** will be hereinafter referred to as a "Bellville ring contact" and the overall contact assembly into which it is placed will be referred to as a "Bellville ring contact assembly".

The embodiment of Belleville ring contact **610** illustrated in FIGS. **16**A and **16**B includes **72** contact members **655** and is preferably in formed from platinized titanium. The contact members **655** may be formed by cutting arcuate sections **657** into the interior diameter of a platinized titanium ring. A predetermined number of the contact members **658** have a greater length than the remaining contact members **655** to, for example, accommodate certain flat-sided wafers.

A further embodiment of a Belleville ring contact **610** is illustrated in FIG. **12**. As above, this embodiment is preferably formed from platinized titanium. Unlike the embodiment of FIGS **11**A and **11**B in which all of the contact members **655** extend radially inward toward the center of the structure, this embodiment includes contact members **659** that are disposed at an angle. This embodiment constitutes a single-piece design that is easy to manufacture and that provides a more compliant contact than does the embodiment of FIGS. **11**A and **11**B with the same footprint. This contact embodiment can be fixtured into the "Belleville" form in the contact assembly and does not require permanent forming. If the Belleville ring contact **610** of this embodiment is fixtured in place, a complete circumferential structure is not required. Rather the contact may be formed and installed in segments thereby enabling independent control/sensing of the electrical properties of the segments.

A first embodiment of a Bellville ring contact assembly is illustrated generally at **600** in in FIGS. **13**–**15**. As illustrated, the contact assembly **600** comprises a conductive contact mount member **605**, a Bellville ring contact **610**, a dielectric wafer guide ring **615**, and an outer body member **625**. The outer, common portion **630** of the Bellville ring contact **610** includes a first side that is engaged within a notch **675** of the conductive base ring **605**. In many respects, the Belleville ring contact assembly of this embodiment is similar in construction with the flexure contact assembly **85** described above. For that reason, the functionality of many of the structures of the contact assembly **600** will be apparent and will not be repeated here.

Preferably, the wafer guide ring **615** is formed from a dielectric material while contact mount member **605** is formed from a single, integral piece of conductive material or from a dielectric or other material that is coated with a conductive material at its exterior. Even more preferably, the conductive ring **605** and Bellville ring contact **610** are formed from platinized titanium or are otherwise coated with a layer of platinum.

The wafer guide ring **615** is dimensioned to fit within the interior diameter of the contact mount member **605**. Wafer guide ring **615** has substantially the same structure as wafer guides **115** and **115***b* described above in connection with contact assemblies **85** and **85***b*, respectively. Preferably, the wafer guide ring **615** includes an annular extension **645** about its periphery that engages a corresponding annular slot **650** of the conductive base ring **605** to allow the wafer guide ring **615** and the contact mount member **605** to snap together.

The outer body member **625** includes an upstanding portion **627**, a transverse portion **629**, a vertical transition portion **632** and a further transverse portion **725** that extends radially and terminates at an upturned lip **730**. Upturned lip **730** assists in forming a barrier to the electroplating environment when it engages the surface of the side of workpiece **25** that is being processed. In the illustrated embodiment, the engagement between the lip **730** and the surface of workpiece **25** is the only mechanical seal that is formed to protect the Bellville ring contact **610**.

The area proximate the contacts **655** of the Belleville ring contact **610** is preferably purged with an inert fluid, such as nitrogen gas, which cooperates with lip **730** to effect a barrier between the Bellville ring contact **610**, peripheral portions and the backside of wafer **25**, and the electroplating environment. As particularly shown set forth in FIGS. **14** and 15, the outer body member 625 and contact mount member 605 are spaced from one another to form an annular cavity 765. The annular cavity 765 is provided with an inert fluid, such as nitrogen, through one or more purge ports 770 disposed through the contact mount member 605. The purged ports 770 open to the annular cavity 765, which functions as a manifold to distribute to the inert gas about the periphery of the contact assembly. A given number of slots, such as at 780, corresponding to the number of contact members 655 are provided and form passages that route the inert fluid from the annular cavity 765 to the area proximate contact members 655.

FIGS. 14 and 15 also illustrate the flow of a purging fluid in this embodiment of Bellville ring contact assembly. As illustrated by arrows, the purge gas enters purge port 770 and is distributed about the circumference of the assembly 600 within annular cavity 765. The purged gas then flows through slots 780 and below the lower end of contact mount member 605 to the area proximate Bellville contact 610. At this point, the gas flows to substantially surround the contact members 655 and, further, may proceed above the periphery of the wafer to the backside thereof. The purging gas may also proceed through an annular channel 712 defined by the contact mount member 605 and the interior of the compliant wall formed at the lower portion of wafer guide ring 615. Additionally, the gas flow about contact members 655 cooperates with upturned lip 730 effect a barrier at lip 730 that prevents electroplating solution from proceeding therethrough.

When a wafer or other workpiece 25 is urged into engagement with the contact assembly 600, the workpiece 25 first makes contact with the contact members 655. As the workpiece is urged further into position, the contact members 655 deflect and effectively wipe the surface of workpiece 25 until the workpiece 25 is pressed against the upturned lip 730. This mechanical engagement, along with the flow of purging gas, effectively isolates the outer periphery and backside of the workpiece 25 as well as the Bellville ring contact 610 from contact with the plating solution.

ROTOR CONTACT CONNECTION ASSEMBLY

In many instances, it may be desirable to have a given reactor assembly 20 function to execute a wide range of solder electroplating recipes. Execution of a wide range of electroplating recipes may be difficult, however, if the process designer is limited to using a single contact assembly construction. Further, the plating contacts used in a given contact assembly construction must be frequently inspected and, sometimes, replaced. This is often difficult to do in existing electroplating reactor tools, frequently involving numerous operations to remove and/or inspect the contact assembly. This problem may be addressed by providing a mechanism by which the contact assembly 85 is readily attached and detached from the other components of the rotor assembly 75. Further, a given contact assembly type can be replaced with the same contact assembly type without re-calibration or readjustment of the system.

To be viable for operation in a manufacturing environment, such a mechanism must accomplish several functions including:

1. Provide secure, fail-safe mechanical attachment of the contact assembly to other portions of the rotor assembly;
2. Provide electrical interconnection between the contacts of the contact assembly and a source of electroplating power;
3. Provide a seal at the electrical interconnect interface to protect against the processing environment (e.g., wet chemical environment);
4. Provide a sealed path for the purge gas that is provided to the contact assembly; and
5. Minimize use of tools or fasteners which can be lost, misplaced, or used in a manner that damages the electroplating equipment.

FIGS. 16 and 17 illustrate one embodiment of a quick-attach mechanism that meets the foregoing requirements. For simplicity, only those portions of the rotor assembly 75 necessary to understanding the various aspects of the quick-attach mechanism are illustrated in these figures.

As illustrated, the rotor assembly 75 may be comprised of a rotor base member 205 and a removable contact assembly 1210. Preferably, the removable contact assembly 1210 is constructed in the manner set forth above in connection with contact assembly 85. The illustrated embodiment, however, employs a continuous ring contact. It will be recognized that both contact assembly constructions are suitable for use with the quick-attachment mechanism set forth herein.

The rotor base member 1205 is preferably annular in shape to match the shape of the semiconductor wafer 25. A pair of latching mechanisms 1215 are disposed at opposite sides of the rotor base member 205. Each of the latching mechanisms 1215 includes an aperture 1220 disposed through an upper portion thereof that is dimensioned to receive a corresponding electrically conductive shaft 1225 that extends downward from the removable contact assembly 1210.

The removable contact assembly 1210 is shown in a detached state in FIG. 16. To secure the removable contact assembly 1210 to the rotor base member 1205, an operator aligns the electrically conductive shafts 1225 with the corresponding apertures 1220 of the latching mechanisms 1215. With the shafts 1225 aligned in this manner, the operator urges the removable contact assembly 1210 toward the rotor base member 1205 so that the shafts 1225 engage the corresponding apertures 1220. Once the removable contact assembly 1210 is placed on the rotor base member 1205, latch arms 1230 are pivoted about a latch arm axis 1235 so that latch arm channels 1240 of the latch arms 1230 engage the shaft portions 1245 of the conductive shafts 1235 while concurrently applying a downward pressure against flange portions 1247. This downward pressure secures the removable contact assembly 1210 with the rotor base assembly 1205. Additionally, as will be explained in further detail below, this engagement results in the creation of an electrically conductive path between electrically conductive portions of the rotor base assembly 1205 and the electroplating contacts of the contact assembly 1210. It is through this path that the electroplating contacts of the contact assembly 1210 are connected to receive power from a plating power supply.

FIGS. 18A and 18B illustrate further details of the latching mechanisms 1215 and the electrically conductive shafts 1225. As illustrated, each latching mechanism 1215 is comprised of a latch body 1250 having aperture 1220, a latch arm 1230 disposed for pivotal movement about a latch arm pivot post 1255, and a safety latch 1260 secured for relatively minor pivotal movement about a safety latch pivot post 1265. The latch body 1250 may also have a purge port 270 disposed therein to conduct a flow of purging fluid to corresponding apertures of the removable contact assembly 210. An O-ring 275 is disposed at the bottom of the flange portions of the conductive shafts 1225 FIGS. 19A–19C are cross-sectional views illustrating operation of the latching mechanisms 1215. As illustrated, latch arm channels 1240 are dimensioned to engage the shaft portions 1245 of the conductive shafts 1225. As the latch arm 1230 is rotated to engage the shaft portions 1245, a nose portion 1280 of the latch arm **1230** cams against the surface **1285** of safety latch **1260** until it mates with channel **1290**. With the nose portion **1280** and corresponding channel **1290** in a mating relationship, latch arm **1230** is secured against inadvertent pivotal movement that would otherwise release removable contact assembly **1210** from secure engagement with the rotor base member **1205**.

FIGS. **20A–20D** are cross-sectional views of the rotor base member **1205** and removable contact assembly **1210** in an engaged state. As can be seen in these cross-sectional views, the electrically conductive shafts **1225** include a centrally disposed bore **1295** that receives a corresponding electrically conductive quick-connect pin **1300**. It is through this engagement that an electrically conductive path is established between the rotor base member **1205** and the removable contact assembly **1210**.

As also apparent from these cross-sectional views, the lower, interior portion of each latch arm **1230** includes a corresponding channel **1305** that is shaped to engage the flange portions **1247** of the shafts **1225**. Edge portions of channel **1305** cam against corresponding surfaces of the flange portions **1247** to drive the shafts **1225** against surface **1310** which, in turn, effects a seal with O-ring **1275**.

ROTOR CONTACT DRIVE

As illustrated in FIGS. **21, 22** and **23**, the rotor assembly **75** includes an actuation arrangement whereby the wafer or other workpiece **25** is received in the rotor assembly by movement in a first direction, and is thereafter urged into electrical contact with the contact assembly by movement of a backing member **310** toward the contact assembly, in a direction perpendicular to the first direction.

As illustrated, the stationary assembly **70** of the reactor head **30** includes a motor assembly **1315** that cooperates with shaft **1320** of rotor assembly **75**. Rotor assembly **75** includes a generally annular housing assembly, including rotor base member **1205** and an inner housing **1320**. As described above, the contact assembly is secured to rotor base member **1205**. By this arrangement, the housing assembly and the contact assembly **1210** together define an opening **1325** through which the workpiece **25** is transversely movable, in a first direction, for positioning the workpiece in the rotor assembly **75**. The rotor base member **1205** preferably defines a clearance opening for the robotic arm as well as a plurality of workpiece supports **3130** upon which the workpiece is positioned by the robotic arm after the workpiece is moved transversely into the rotor assembly by movement through opening **1325**. The supports **1330** thus support the workpiece **25** between the contact assembly **1210** and the backing member **1310** before the backing member engages the workpiece and urges it against the contact ring.

Reciprocal movement of the backing member **1310** relative to the contact assembly **1210** is effected by at least one spring which biases the backing member toward the contact assembly, and at least one actuator for moving the backing member in opposition to the spring. In the illustrated embodiment, the actuation arrangement includes an actuation ring **1335** which is operatively connected with the backing member **1310**, and which is biased by a plurality of springs, and moved in opposition to the springs by a plurality of actuators.

With particular reference to FIG. **21**, actuation ring **1335** is operatively connected to the backing member **1310** by a plurality (three) of shafts **1340**. The actuation ring, in turn, is biased toward the housing assembly by three compression coil springs **1345** which are each held captive between the actuation ring and a respective retainer cap **350**. By this arrangement, the action of the biasing springs **1345** urges the actuation ring **1335** in a direction toward the housing, with the action of the biasing springs thus acting through shafts **1340** to urge the backing member **1335** in a direction toward the contact assembly **1210**. The drive shaft **1360** is operatively connected to inner housing **1320** for effecting rotation of workpiece **25**, as it is held between contact assembly **210** and backing member **310**, during plating processing. The drive shaft **360**, in turn, is driven by motor **315** that is disposed in the stationary portion of the reactor head **30**.

Rotor assembly **75** is preferably detachable from the stationary portion of the reactor head **30** to facilitate maintenance and the like. Thus, drive shaft **1360** is detachably coupled with the motor **1315**. In accordance with the preferred embodiment, the arrangement for actuating the backing member **1310** also includes a detachable coupling, whereby actuation ring **1335** can be coupled and uncoupled from associated actuators which act in opposition to biasing springs **1345**.

Actuation ring **1335** includes an inner, interrupted coupling flange **1365**. Actuation of the actuation ring **1335** is effected by an actuation coupling **1370** of the stationary assembly **70**, which can be selectively coupled and uncoupled from the actuation ring **1335**. The actuation coupling **1370** includes a pair of flange portions **1375** which can be interengaged with coupling flange **1365** of the actuation ring **1335** by limited relative rotation therebetween. By this arrangement, the actuation ring **1335** of the rotor assembly **75** can be coupled to, and uncoupled from, the actuation coupling **1370** of the stationary assembly **70** of the reactor head **30**.

Actuation coupling **370** is movable in a direction in opposition to the biasing springs **1345** by a plurality of pneumatic actuators **1380** mounted on a frame of the stationary assembly **70**. Each actuator **1380** is operatively connected with the actuation coupling **1370** by a respective drive member **1385**, each of which extends generally through the frame of the stationary assembly **70**.

There is a need to isolate the foregoing mechanical components from other portions of the reactor assembly **20**. A failure to do so will result in contamination of the processing environment (here, a wet chemical electroplating environment). Additionally, depending on the particular process implemented in the reactor **20**, the foregoing components can be adversely affected by the processing environment.

To effect such isolation, a bellows assembly **1390** is disposed to surround the foregoing components. The bellows assembly **1390** comprises a bellows member **1395**, preferably made from Teflon, having a first end thereof secured at **1400** and a second end thereof secured at **1405**. Such securement is preferably implemented using the illustrated liquid-tight, tongue-and-groove sealing arrangement. The convolutes **1410** of the bellows member **1395** flex during actuation of the backing plate **1310**.

WAFER LOADING/PROCESSING OPERATIONS

Operation of the reactor head **30** will be appreciated from the above description. Loading of workpiece **25** into the rotor assembly **75** is effected with the rotor assembly in a generally upwardly facing orientation, such as illustrated in FIG. **3**. Workpiece **25** is moved transversely through the opening **325** defined by the rotor assembly **75** to a position wherein the workpiece is positioned in spaced relationship generally above supports **1330**. A robotic arm **415** is then lowered (with clearance opening **325** accommodating such movement), whereby the workpiece is positioned upon the supports **1330**. The robotic arm **415** can then be withdrawn from within the rotor assembly **75**.

The workpiece **25** is now moved perpendicularly to the first direction in which it was moved into the rotor assembly. Such movement is effected by movement of backing member **1310** generally toward contact assembly **1210**. It is presently preferred that pneumatic actuators **1380** act in opposition to biasing springs **1345** which are operatively connected by actuation ring **1335** and shafts **1340** to the backing member **1310**. Thus, actuators **1380** are operated to permit springs **1345** to bias and urge actuation ring **1335** and, thus, backing member **1310**, toward contact **210**. FIG. **12** illustrates the disposition of the reactor head **30** in a condition in which it may accept a workpiece, while FIG. **22** illustrates the disposition of the reactor head and a condition in which it is ready to present though workpiece to the reactor bowl **35**.

In the preferred form, the connection between actuation ring **1335** and backing member **1310** by shafts **1340** permits some "float". That is, the actuation ring and backing member are not rigidly joined to each other. This preferred arrangement accommodates the common tendency of the pneumatic actuators **1380** to move at slightly different speeds, thus assuring that the workpiece is urged into substantial uniform contact with the electroplating contacts of the contact assembly **1210** while avoiding excessive stressing of the workpiece, or binding of the actuation mechanism.

With the workpiece **25** firmly held between the backing member **1310** and the contact assembly **1210**, lift and rotate apparatus **80** rotates the reactor head **30** and lowers the reactor head into a cooperative relationship with reactor bowl **35** so that the surface of the workpiece is placed in contact with the surface of the plating solution (i.e., the meniscus of the plating solution) within the reactor vessel. FIG. **1** illustrates the apparatus in this condition. If a contact assembly such as contact assembly **85** is used in the reactor **20**, the contact assembly **85** seals the entire peripheral region of the workpiece. Depending on the particular electroplating process implemented, it may be useful to insure that any gas which accumulates on the surface of the workpiece is permitted to vent and escape. Accordingly, the surface of the workpiece may be disposed at an acute angle, such as on the order of two degrees from horizontal, with respect to the surface of the solution in the reactor vessel. This facilitates venting of gas from the surface of the workpiece during the plating process as the workpiece, and associated backing and contact members, are rotated during processing. Circulation of plating solution within the reactor bowl **35**, as electrical current is passed through the workpiece and the plating solution, effects the desired electroplating of the solder on the surface of the workpiece.

A number of features of the present reactor facilitate efficient and cost-effective electroplating of of solder on workpieces such as semiconductor wafers. By use of a contact assembly having substantially continuous contact in the form of a large number of sealed, compliant discrete contact regions, a high number of plating contacts are provided while minimizing the required number of components. The actuation of the backing member **1310** is desirably effected by a simple linear motion, thus facilitating precise positioning of the workpiece, and uniformity of contact with the contact ring. The isolation of the moving components using a bellows seal arrangement further increases the integrity of the electroplating process.

Maintenance and configuration changes are easily facilitated through the use of a detachable contact assembly **1210**. Further, maintenance is also facilitated by the detachable configuration of the rotor assembly **75** from the stationary assembly **70** of the reactor head. The contact assembly provides excellent distribution of electroplating power to the surface of the workpiece, while the preferred provision of the peripheral seal protects the contacts from the plating environment (e.g., contact with the plating solution), thereby desirably preventing build-up of solder onto the electrical contacts. The perimeter seal also desirably prevents plating onto the peripheral portion of the workpiece.

INTEGRATED PLATING TOOL

FIGS. **24** through **26** are top plan views of integrated processing tools, shown generally at **1450**, **1455**, and **1500** that may incorporate electroless plating reactors and electroplating reactors as a combination for plating on a microelectronic workpiece, such as a semiconductor wafer. Processing tools **1450** and **1455** are each based on tool platforms developed by Semitool, Inc., of Kalispell, Mont. The processing tool platform of the tool **450** is sold under the trademark LT-210™, the processing tool platform of the tool **1455** is sold under the trademark LT-210C™, and the processing tool **1500** is sold under the trademark EQUINOX™. The principal difference between the tools **1450**, **1455** is in the footprints required for each. The platform on which tool **1455** is based has a smaller footprint than the platform on which tool **1455** is based. Additionally, the platform on which tool **1450** is based is modularized and may be readily expanded. Each of the processing tools **1450**, **4155**, and **1500** are computer programmable to implement user entered processing recipes.

Each of the processing tools **1145**, **1455**, and **1500** include an input/output section **1460** a processing section **1465**, and one or more robots **1470**. The robots **1470** for the tools **1450** **1455** move along a linear track. The robot **1470** for the tool **1500** is centrally mounted and rotates to access the input/output section **1460** and the processing section **1465**. Each input/output section **1460** is adapted to hold a plurality of workpieces, such as semiconductor wafers, in one or more workpiece cassettes. Processing section **1465** includes a plurality of processing stations **1475** that are used to perform one or more fabrication processes on the semiconductor wafers. The robots **1470** are used to transfer individual wafers from the workpiece cassettes at the input/output section **1460** to the processing stations **1475**, as well as between the processing stations **1475**.

One or more of the processing stations **1475** are configured as electroplating assemblies, such as the electroplating assembly described above, for electroplating solder onto the semiconductor wafers. For example, each of the processing tools **1450** and **1455** may include eight solder plating reactors and a single pre-wet/rinse station. The pre-wet/rinse station is preferably one of the type available from Semitool, Inc. Alternatively, each of the processing tools **1450** and **1455** may be configured to plate copper studs onto the semiconductor wafers and plate solder, such as eutectic solder, over the copper studs. In such instances, for example, five of the processing stations **1475** may be configured to plate eutectic solder, one of the stations may be configured to plate the copper studs, one of the stations may be configured to execute a pre-wet/rinse process, and one of the stations may be configured as a spin rinser/dryer (SRD). Still further, each of the processing tools **1450** and **1455** may be configured to plate two different types of solder (e.g., eutectic solder and high lead solder). It will now be recognized that a wide variation of processing station configurations may be used in each of the individual processing tools **1450**, **1455** and **1500** to execute pre-solder electroplating and post-solder electroplating processes. As such, the foregoing configurations are merely illustrative of the variations that may be used.

Numerous modifications may be made to the foregoing system without departing from the basic teachings thereof. Although the present invention has been described in substantial detail with reference to one or more specific embodiments, those of skill in the art will recognize that changes may be made thereto without departing from the scope and spirit of the invention as set forth in the appended claims.

What is claimed is:

1. An apparatus for plating solder on a microelectronic workpiece comprising:

a reactor chamber adapted to hold an electroplating solution comprising an aqueous solution including a lead compound as a source of lead ions and a tin compound as a source of tin ions;

a chemical delivery system adapted to provide the electroplating solution comprising the aqueous solution including the lead compound and the tin compound to the reactor chamber at a high flow rate;

a workpiece support including a contact assembly for providing electroplating power to a surface at a side of the workpiece that is to be plated, the contact arranged for contacting the workpiece at a large plurality of discrete contact points, the contact points being isolated from exposure to the electroplating solution;

a consumable anode comprised of a metal selected from the group consisting of tin and lead, the consumable anode being spaced from the workpiece support within the reaction chamber and positioned for contact with the electroplating solution.

2. An apparatus as claimed in claim **1** wherein the chemical delivery system is adapted to supply an electroplating solution that further comprises methane sulfonic acid.

3. An apparatus as claimed in claim **1** at wherein the consumable anode is comprised of lead.

4. An apparatus as claimed in claim **1** wherein the consumable anode is comprised of tin.

5. Apparatus as claimed in claim reference claim **1** wherein the contact assembly comprises:

a plurality of contacts disposed to contact a peripheral edge of the surface of the workpiece, the plurality of contacts executing a wiping action against the surface of the workpiece as the workpiece is brought into engagement therewith, and

a barrier disposed interior of the plurality of contacts and including a member disposed to engage the surface of the workpiece to effectively isolate the plurality of contacts from the electroplating solution.

6. A reactor as claimed in claim **5** wherein the plurality of contacts are in the form of discrete flexures.

7. A reactor as claimed in claim **5** wherein the plurality of contacts are in the form a Belleville ring contact.

8. A reactor as claimed in claim **5** and further comprising a flow path disposed in the contact assembly, the flow path being adapted to provide a purging gas to the plurality of contacts and the peripheral edge of the workpiece.

9. A reactor as claimed in claim **8** wherein the flow path is connected to a source of purging gas to thereby assist in isolating the plurality of contacts from the electroplating solution.

10. An apparatus for plating solder on a microelectronic workpiece comprising:

a moveable head including a rotor and rotor drive adapted to rotate the workpiece during processing thereof;

a processing base adapted to hold an aqueous electroplating solution including a concentration of lead ions and a concentration of tin ions;

a chemical delivery system connected to deliver the aqueous electroplating solution including a concentration of lead ions and a concentration of tin ions to the processing base at a high flow rate;

a contact assembly disposed on the rotor of the moveable head, the contact assembly providing electroplating power to a peripheral edge surface of a side of the workpiece that is to be plated, the contact assembly contacting the workpiece at a large plurality of discrete contact points, the contact points being sealed from exposure to the electroplating solution;

an actuator disposed to move the moveable head between a loading position in which the workpiece may be placed for support on the rotor and into engagement with the contact, and a processing position in which the surface of the workpiece that is to be electroplated is brought into contact with the electroplating solution with the side of the wafer that is to be processed in a face down orientation during electroplating;

a consumable anode disposed in the processing base and positioned for contact with the electroplating solution, the consumable anode comprising a metal selected from the group consisting of lead and tin.

11. An apparatus as claimed in claim **10** wherein the chemical delivery system is adapted to provide an electroplating solution that further comprises methane sulfonic acid.

12. An apparatus as claimed in claim **10** wherein the anode is comprised of lead.

13. An apparatus as claimed in claim **10** wherein the anode is comprised of tin.

14. Apparatus as claimed in claim reference claim **10** wherein the contact assembly comprises:

a plurality of contacts disposed to contact a peripheral edge of the surface of the workpiece, the plurality of contacts executing a wiping action against the surface of the workpiece as the workpiece is brought into engagement therewith, and

a barrier disposed interior of the plurality of contacts and including a member disposed to engage the surface of the workpiece to effectively isolate the plurality of contacts from the electroplating solution.

15. A reactor as claimed in claim **14** wherein the plurality of contacts are in the form of discrete flexures.

16. A reactor as claimed in claim **14** wherein the plurality of contacts are in the form of a Belleville ring contact.

17. A reactor as claimed in claim **14** and further comprising a flow path disposed in the contact assembly, said flow path being adapted to conduct a flow of a purging gas to the plurality of contacts and the peripheral edge of the workpiece.

18. A reactor as claimed in claim **17** wherein the flow path is connected to a source of purging gas to thereby assist in isolating the plurality of contacts from the electroplating solution.

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